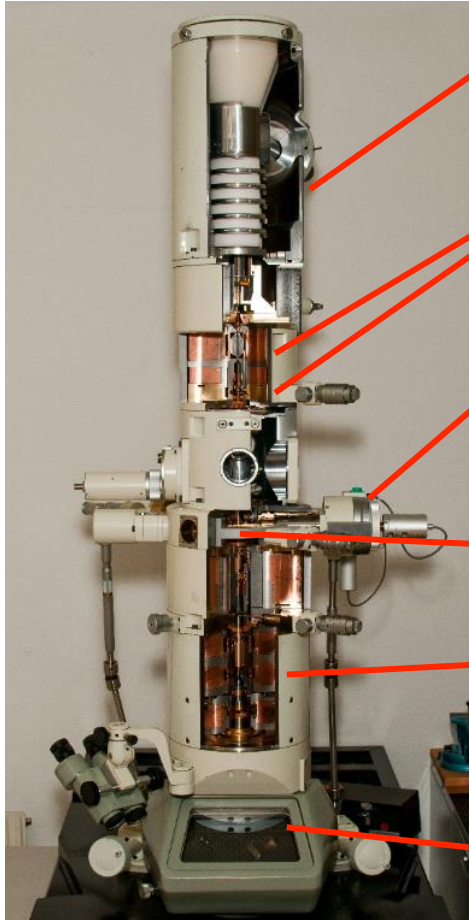


Imaging modes in TEM

November 2019

**Electron Source**

Produces high energy, large current, and high coherence electron beams necessary for generating diffraction patterns and high spatial resolution images

Condenser system and condenser aperture

Controls spot size and illumination area on sample (beam intensity)

Specimen holder and goniometer**Objective lens and objective aperture**

Images sample and is the strongest lens in the system

Intermediate and projector lenses

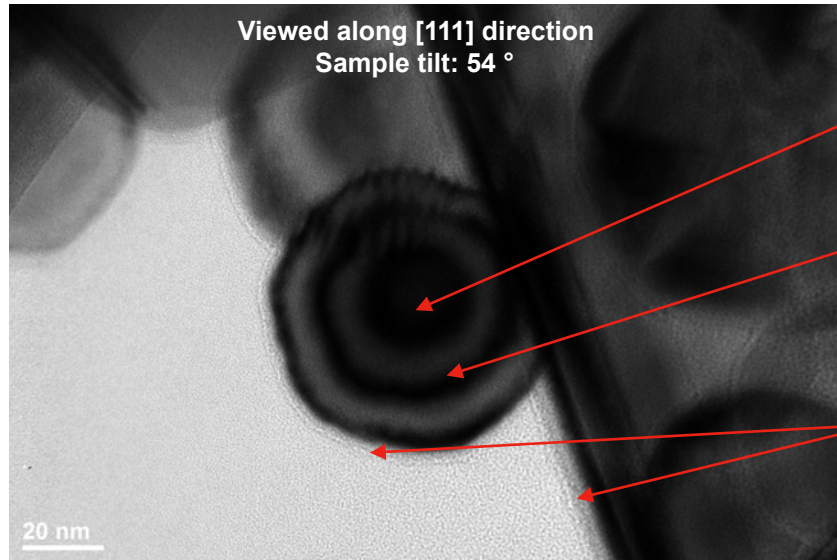
Changes modes from diffraction to imaging
Controls magnification

Detectors / Camera

Various different configurations designed to collect signals produced by the high-energy electron beam

EPFL What do you see in this image and how to interpret the contrast?

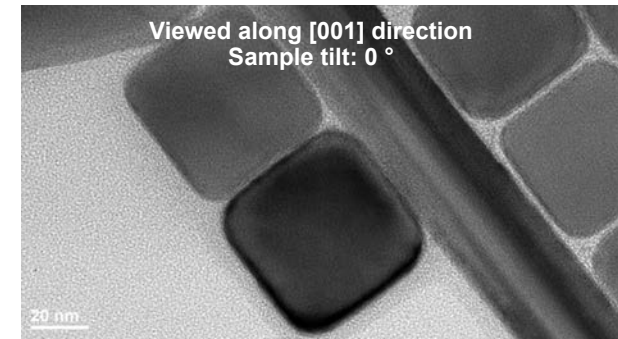
- 1- Why cubic particles appear as hexagons?
- 2- Why Cu particles are darker than the carbon background?
- 3- Why the middle particle is darker than the rest?
- 4- What is the origin of dark oscillatory contrast inside the Cu particles?
- 5- What are the bright (could be dark) fringes at the edge of particles?



3- Diffraction contrast

4- Dynamical diffraction effect

5- Phase contrast
(Fresnel fringes)



Bright-field TEM image of 54 nm cubic Cu particles

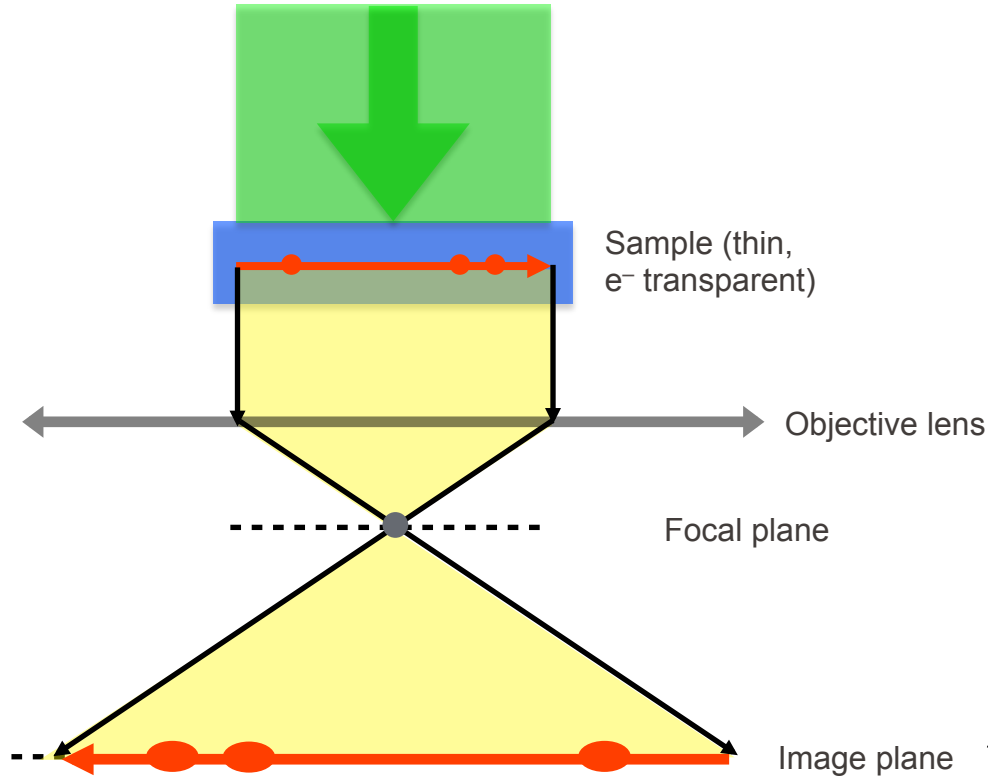
■ Image formation in TEM

- Image and diffraction modes
- Bright- and dark-field modes
 - Strong- and weak-beam
- High-resolution TEM

■ Image contrast in TEM

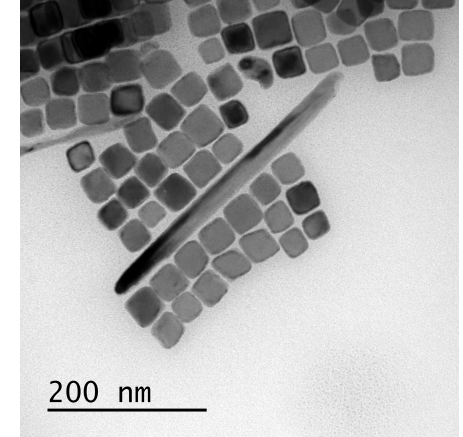
- Mass-thickness contrast
- Diffraction contrast
- Phase contrast

Parallel incident e^- beam; $\lambda \approx 0.02\text{--}0.03 \text{ \AA}$



Why some cubic particles appear darker than others?

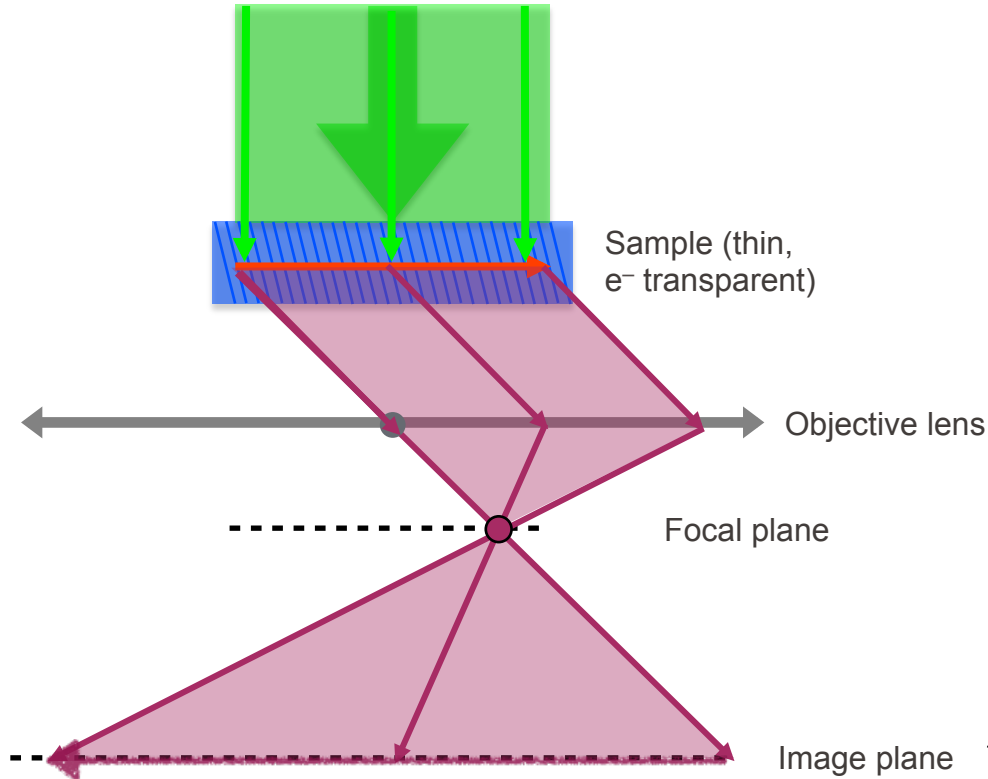
Cubic particles ($\approx 40 \text{ nm}$) of Cu



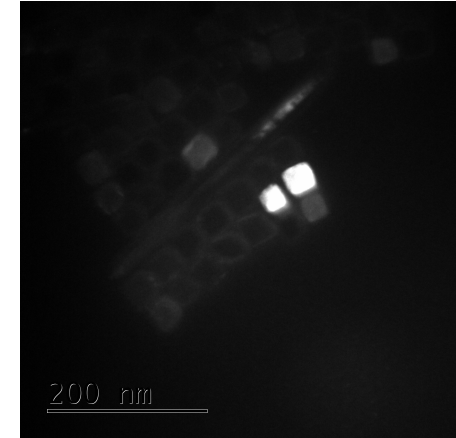
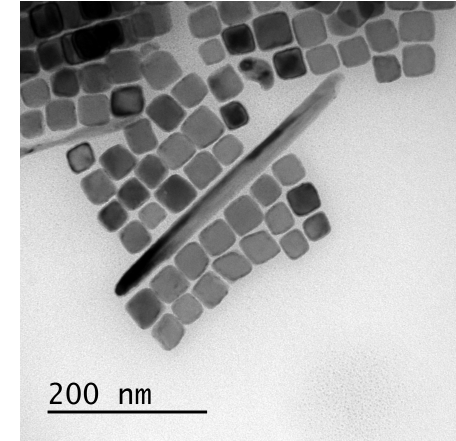
Bright-field image:
made by directly transmitted electrons

Image formation in TEM

Parallel incident e^- beam; $\lambda \approx 0.02\text{--}0.03 \text{ \AA}$



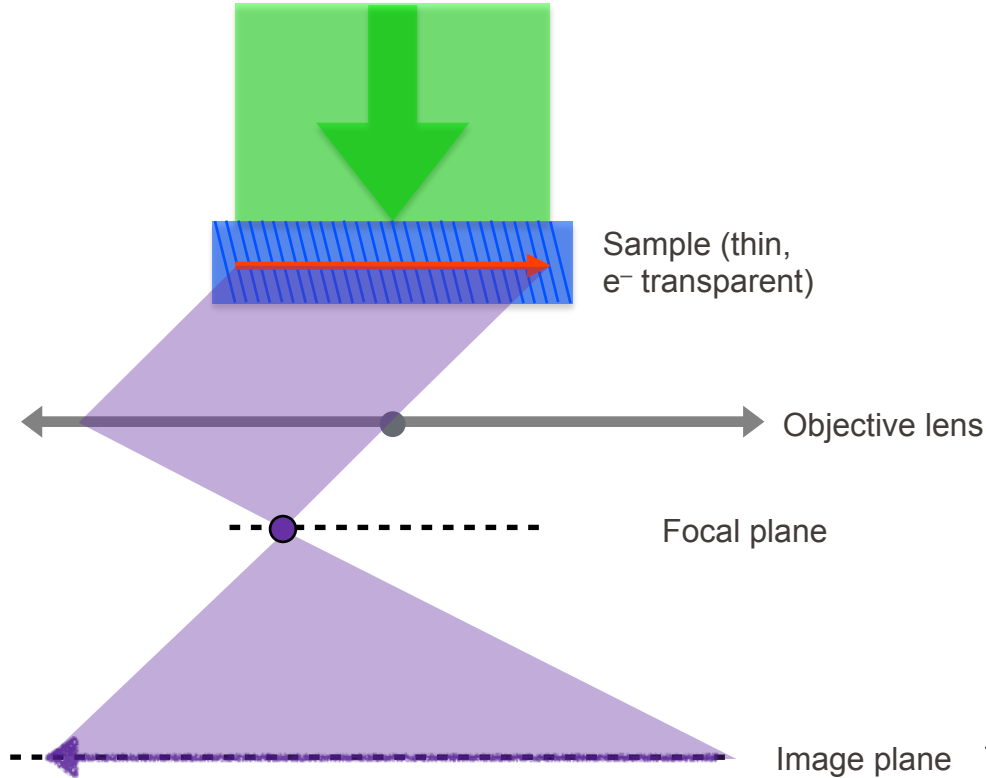
Bright-field image



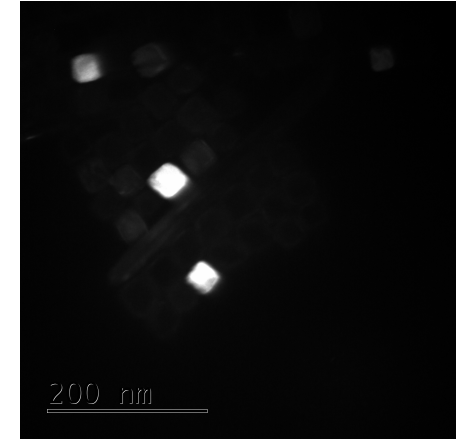
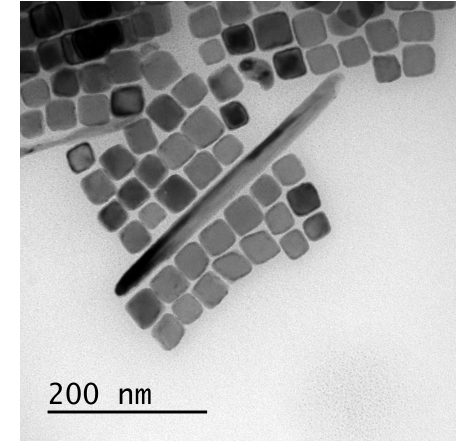
Dark-field image:
made by selected diffracted electrons

Image formation in TEM

Parallel incident e^- beam; $\lambda \approx 0.02\text{--}0.03 \text{ \AA}$



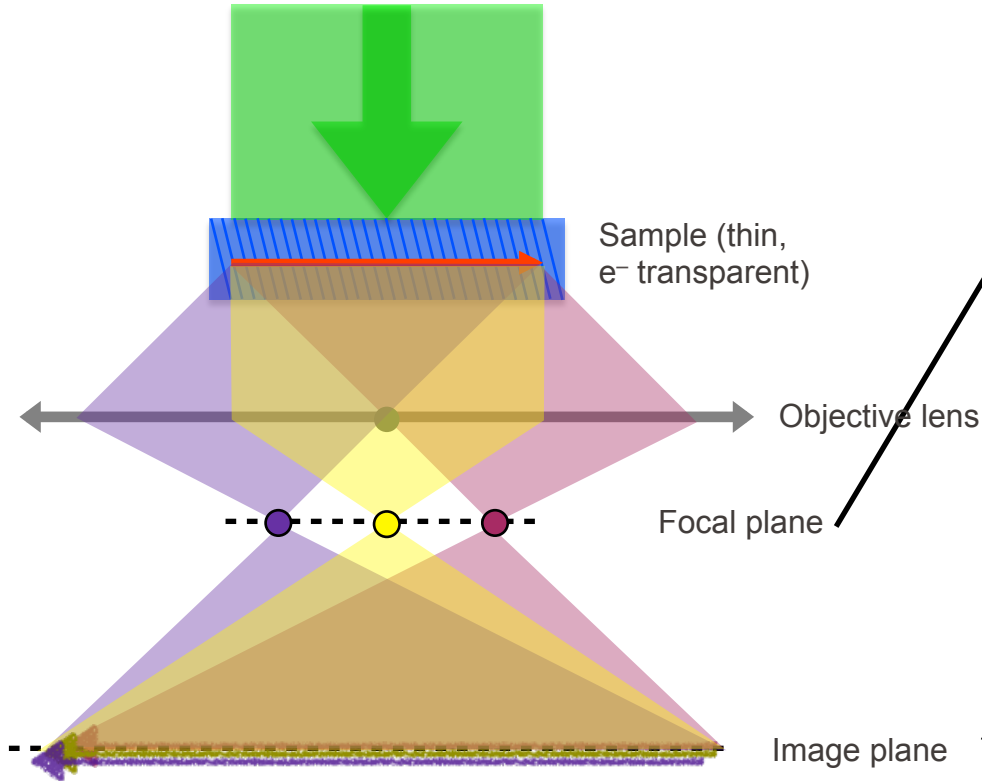
Bright-field image



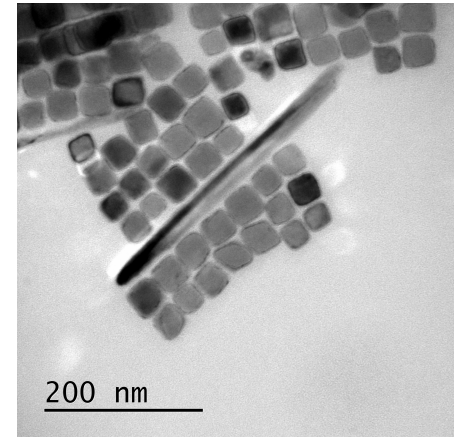
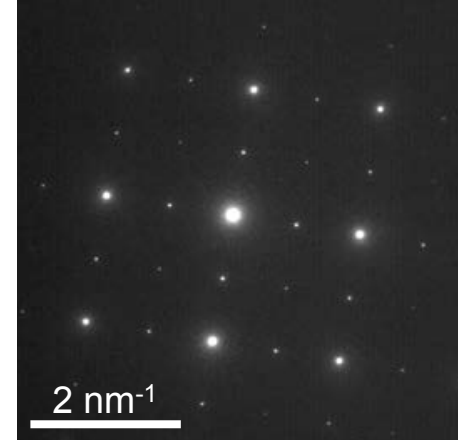
Dark-field image:
made by selected diffracted electrons

Image formation in TEM

Parallel incident e^- beam; $\lambda \approx 0.02\text{--}0.03 \text{ \AA}$



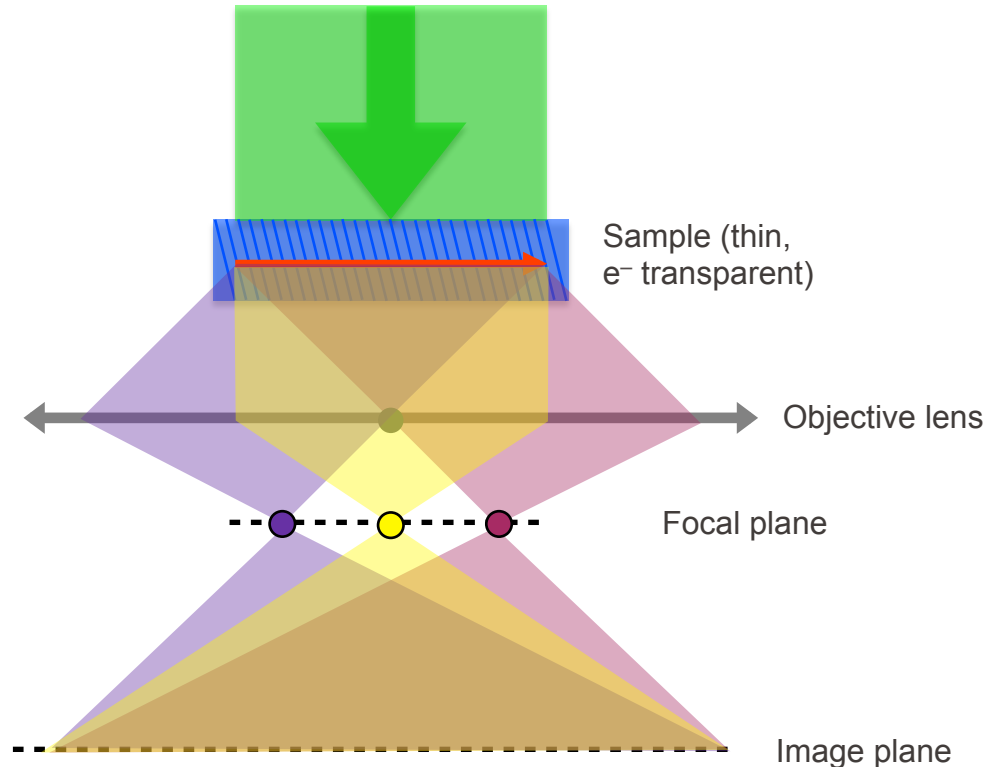
Electron diffraction pattern



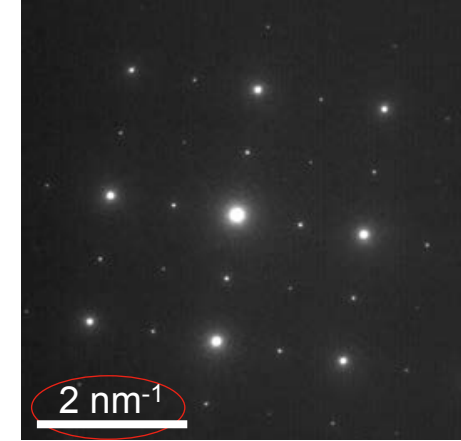
Ghost image:
Superposition of images made
by direct and diffracted electrons

Image formation in TEM

Parallel incident e^- beam; $\lambda \approx 0.02\text{--}0.03 \text{ \AA}$

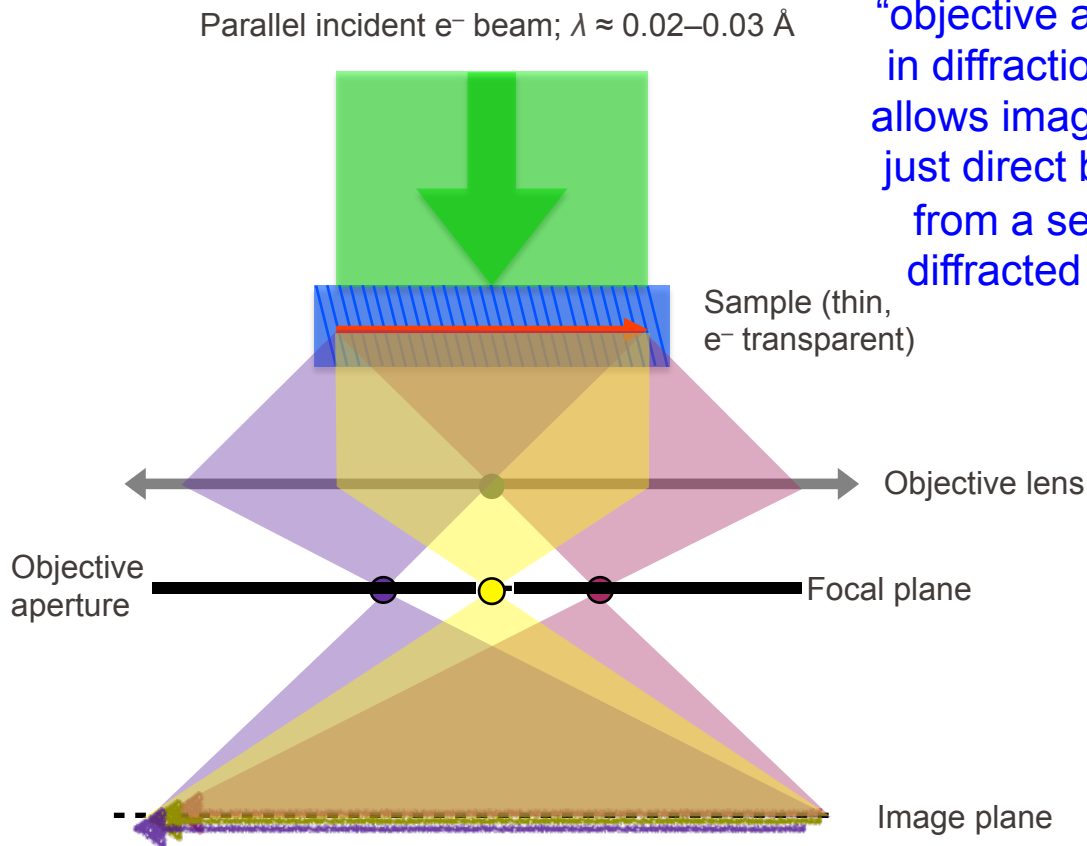


Electron diffraction pattern



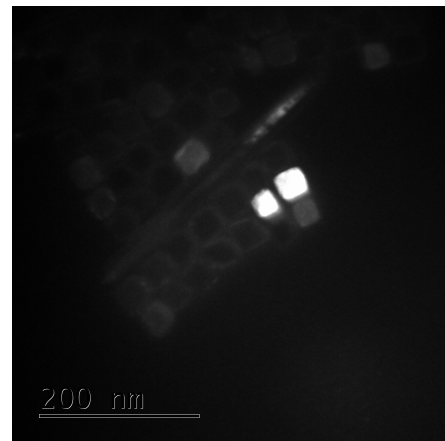
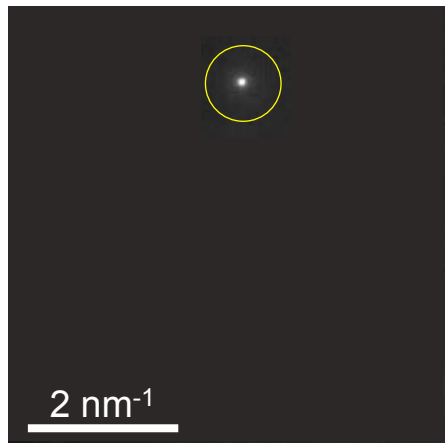
- *In back focal plane of objective lens parallel rays focused to point*
- *Diffraction – coherent scattering – creates sets of parallel rays from different crystal planes*
- *Focusing of these parallel rays in back focal plane creates spots of strong intensity:
the diffraction pattern*

Image formation in TEM

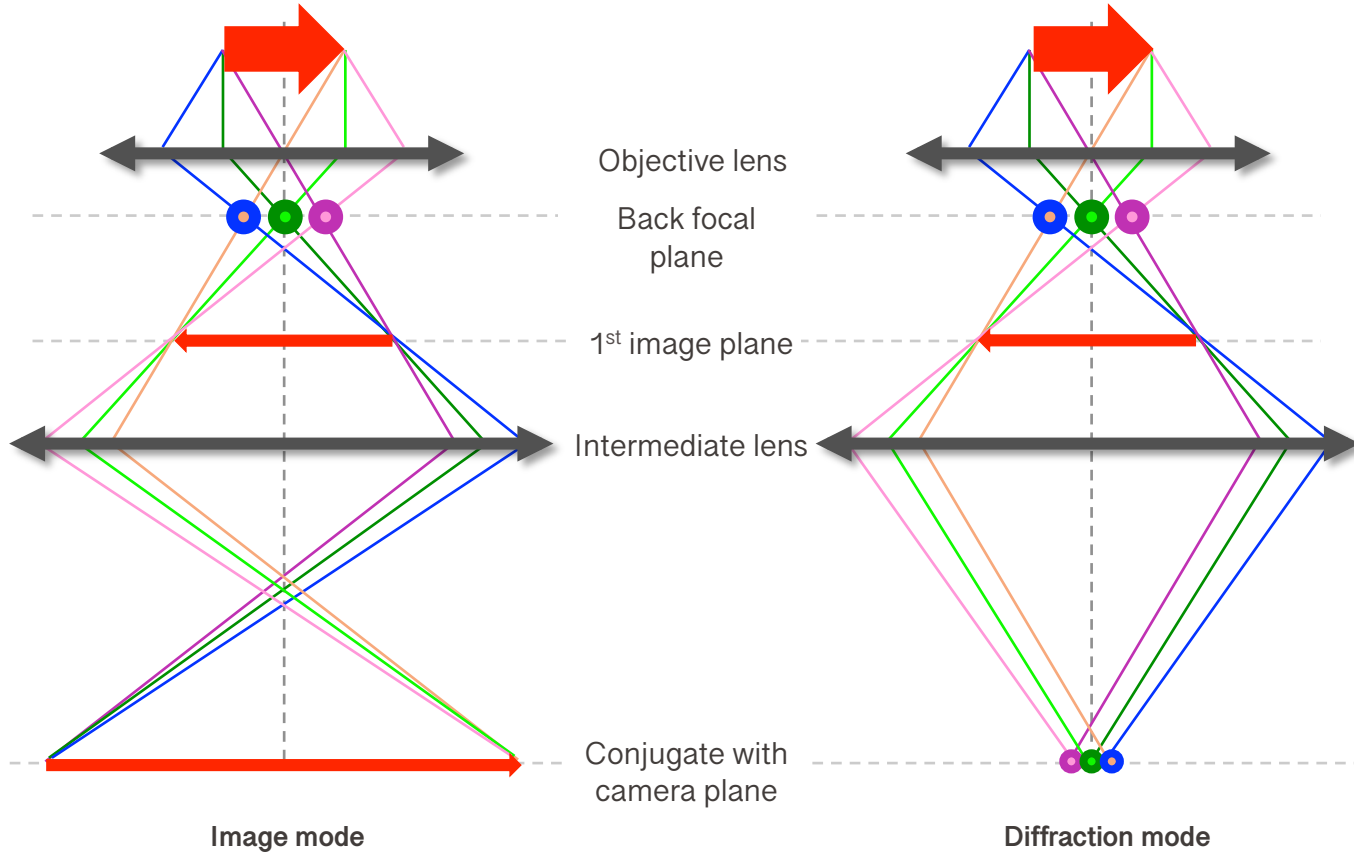


Insertion of the “objective aperture” in diffraction plane allows imaging from just direct beam or from a selected diffracted beam.

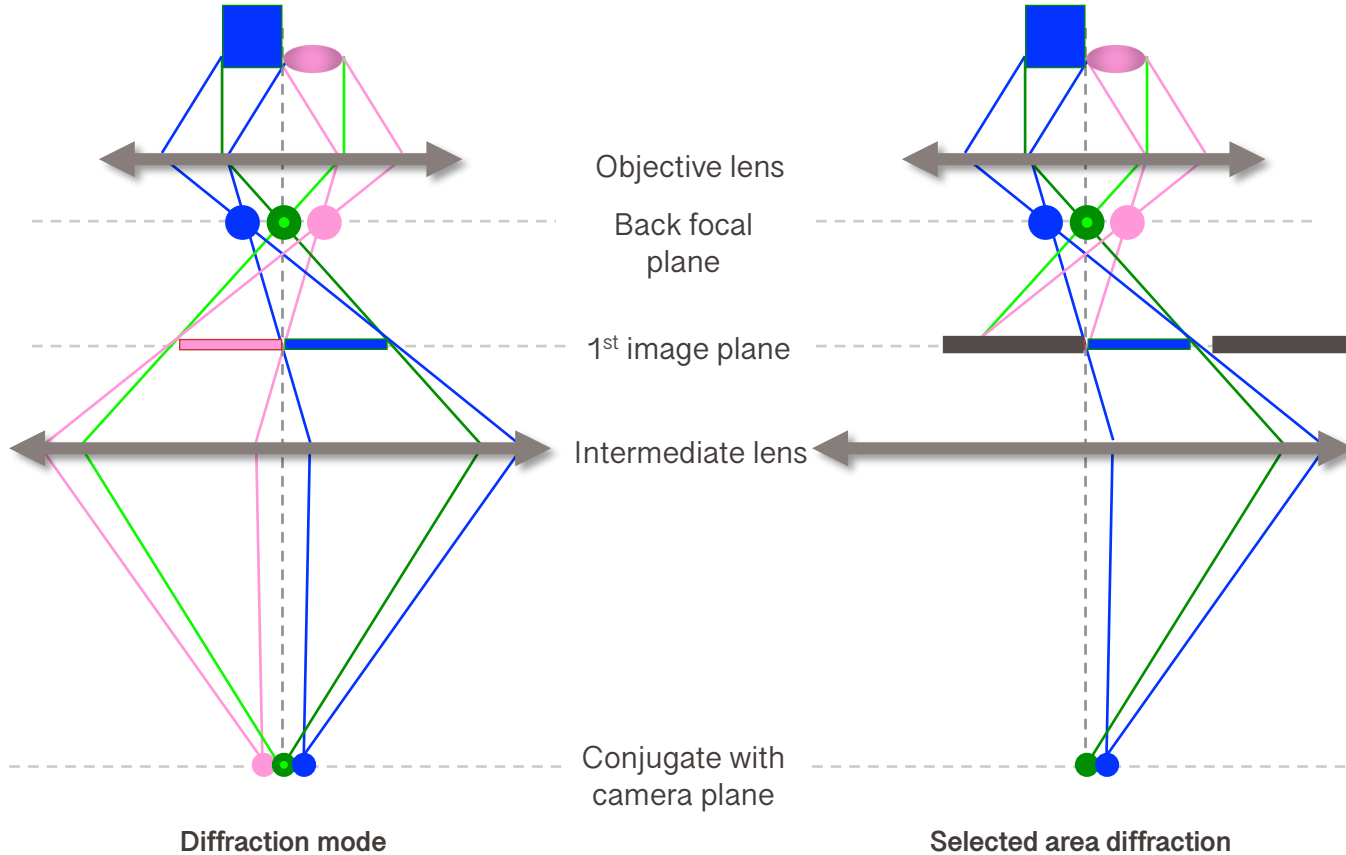
Electron diffraction pattern



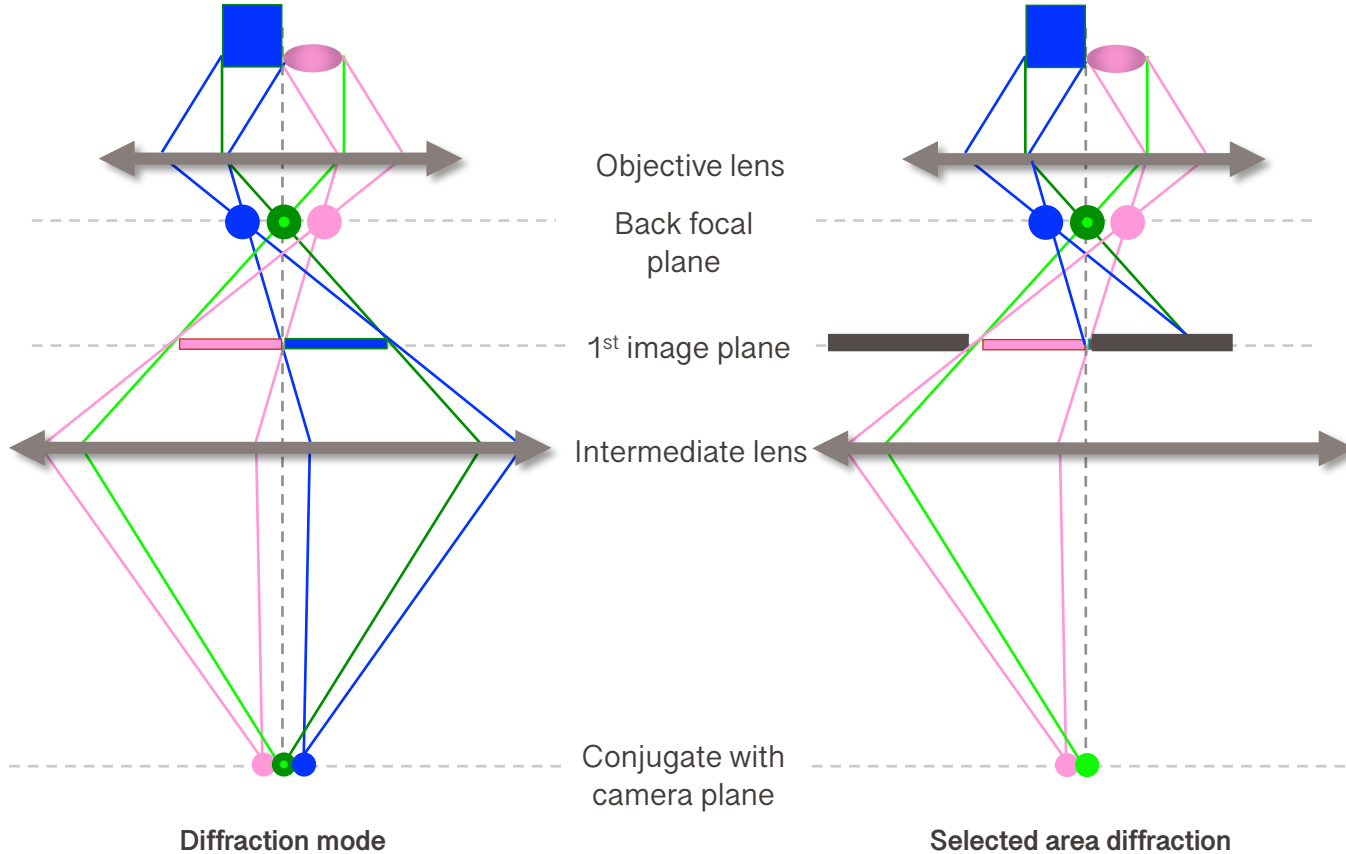
Dark-field image: made by selected diffracted electrons by direct and diffracted electrons



Imaging modes: Selected area electron diffraction

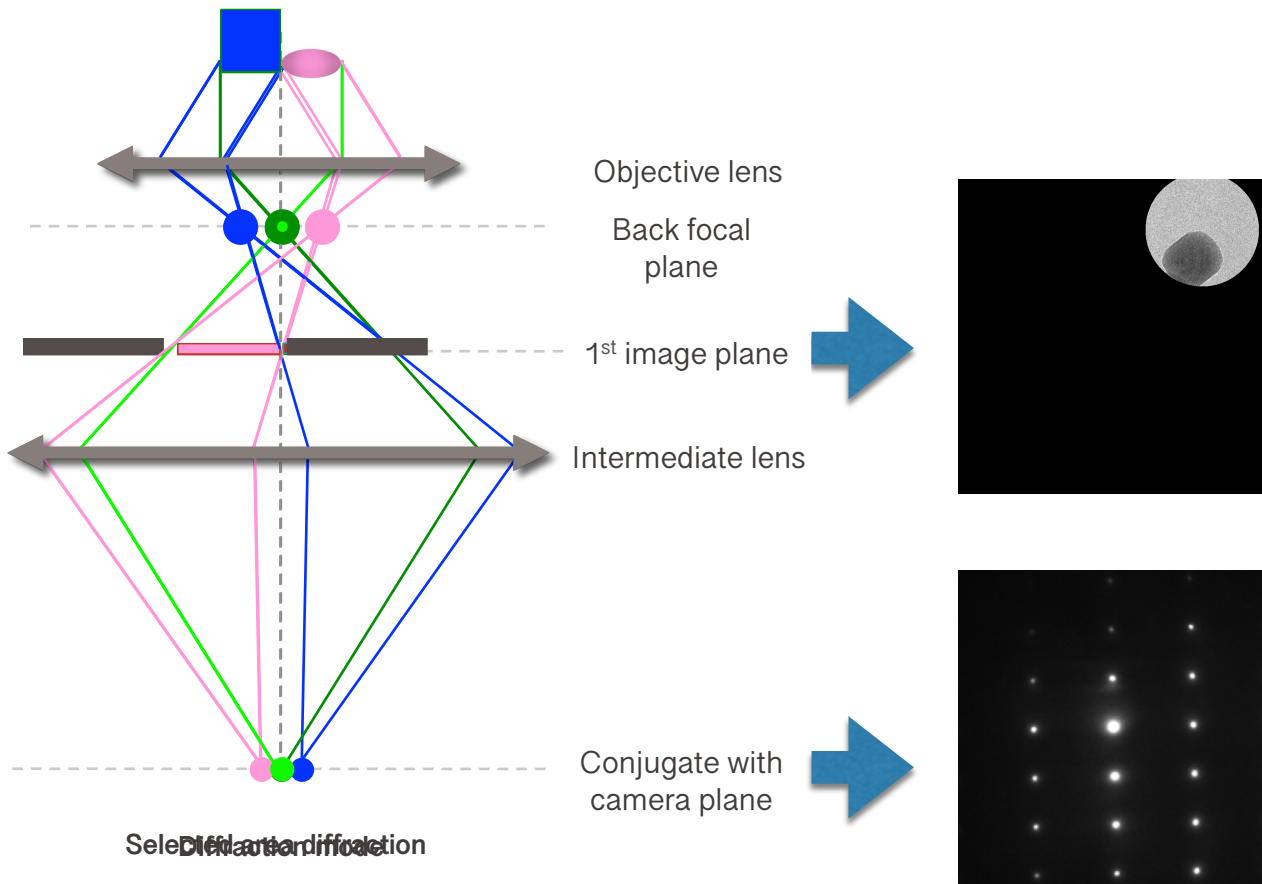


Imaging modes: Selected area electron diffraction



Imaging modes:

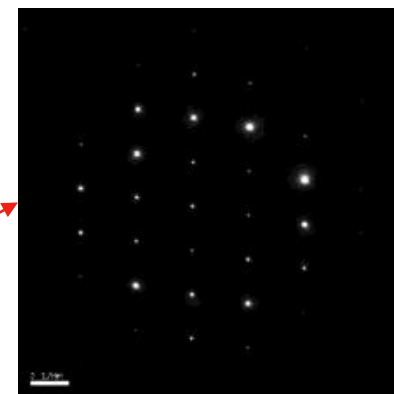
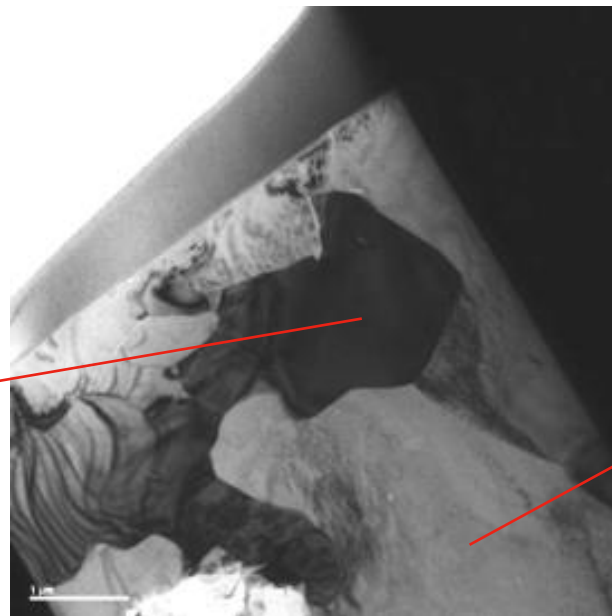
Selected area electron diffraction



Imaging modes: Selected area electron diffraction



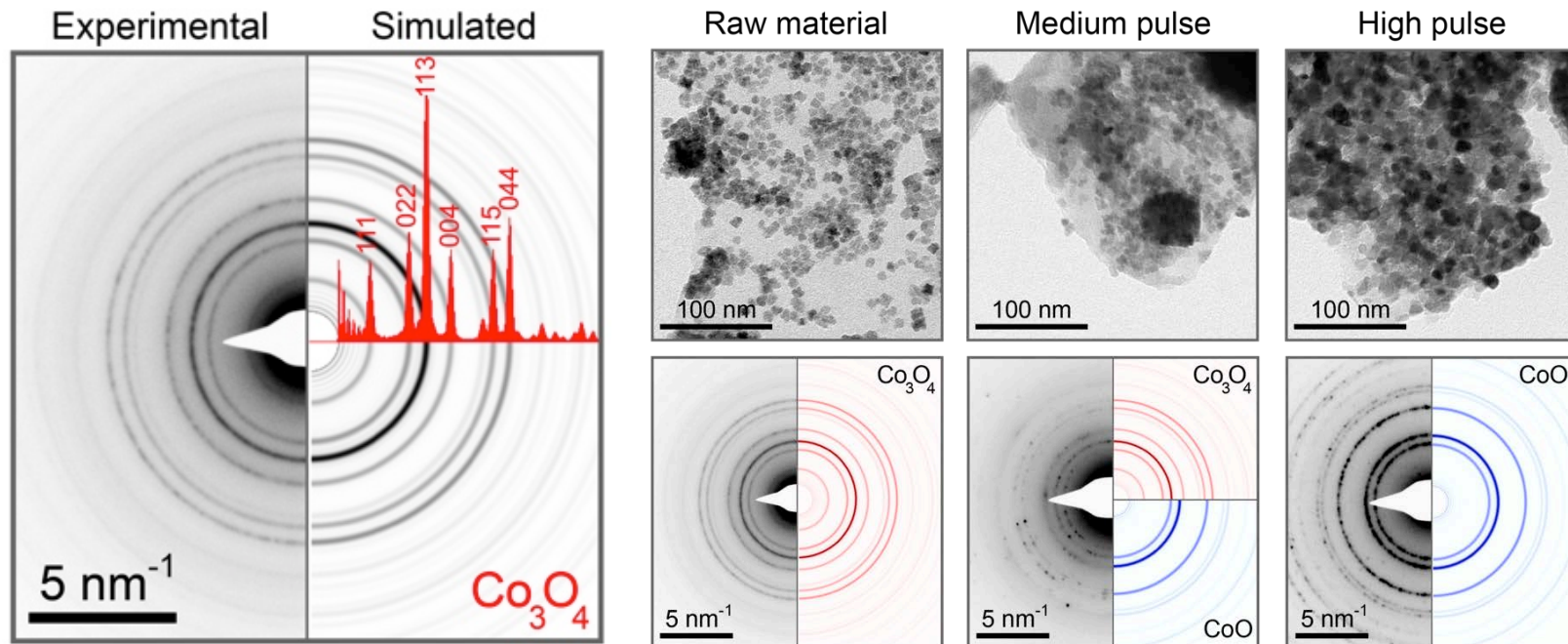
Monoclinic Al_3Fe



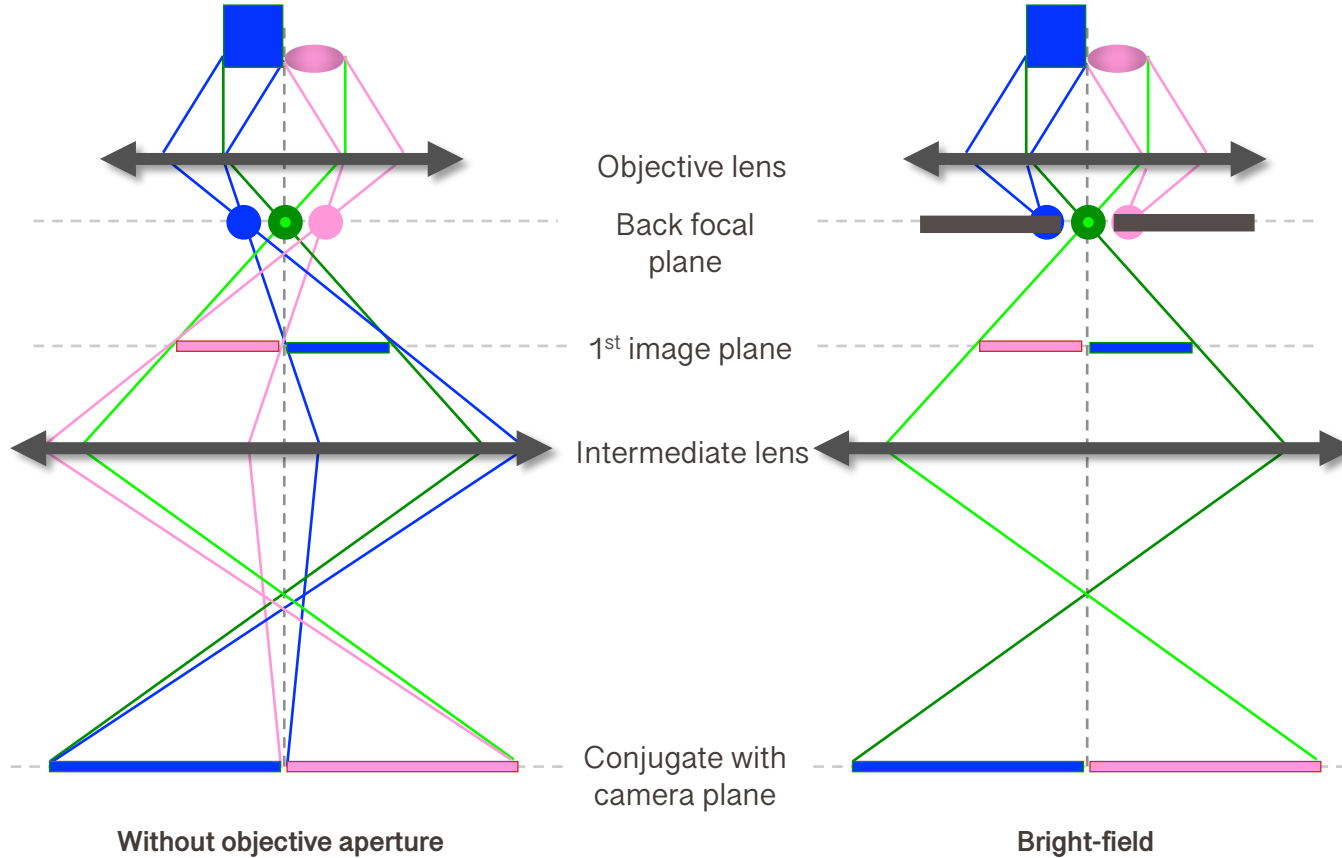
Hexagonal $\alpha\text{-(AlFeSi)}$

Imaging modes: Selected area electron diffraction

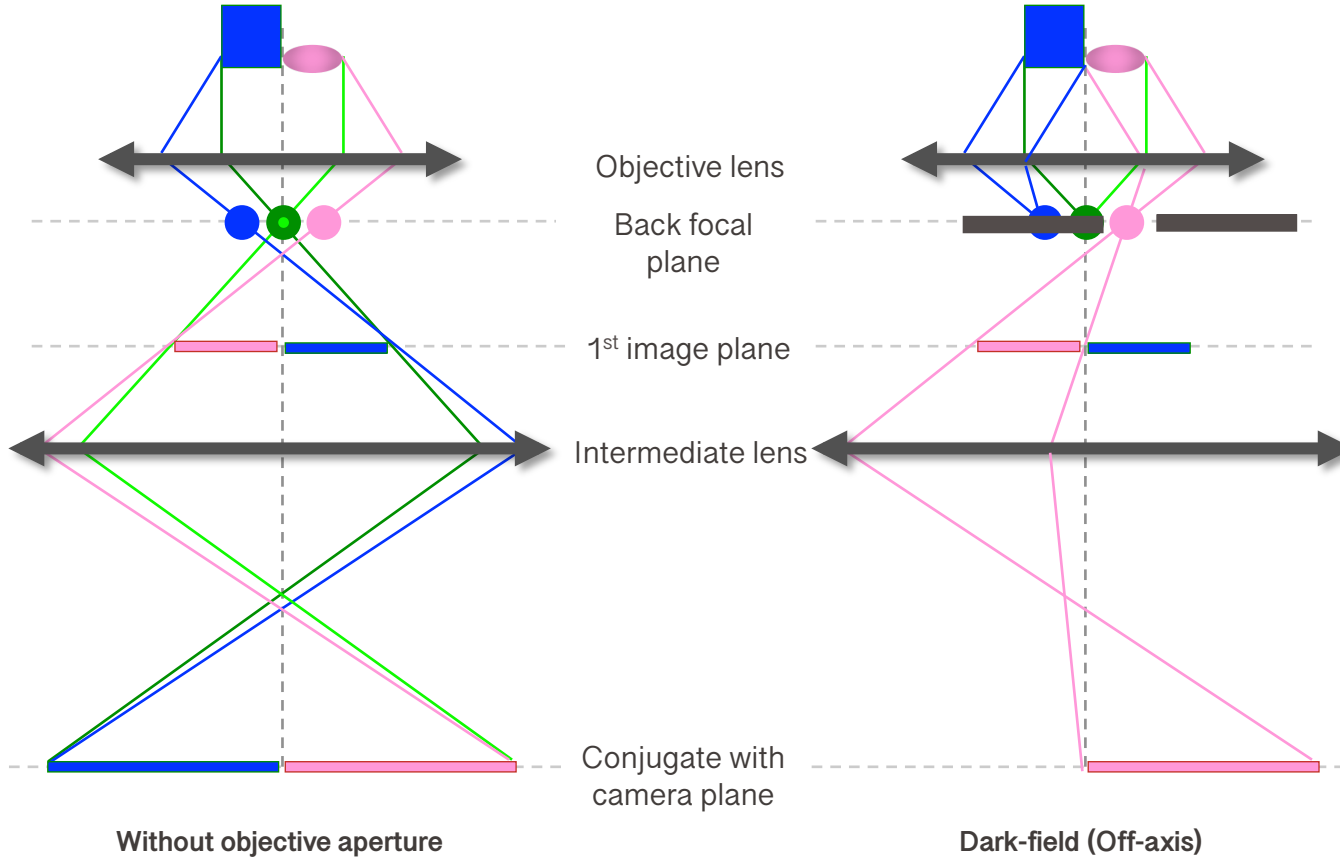
Example: Rapid inkjet printing of $\text{Co}_3\text{O}_4/\text{N-rGO}$ layers for oxygen reduction reaction



Imaging modes: Bright-field



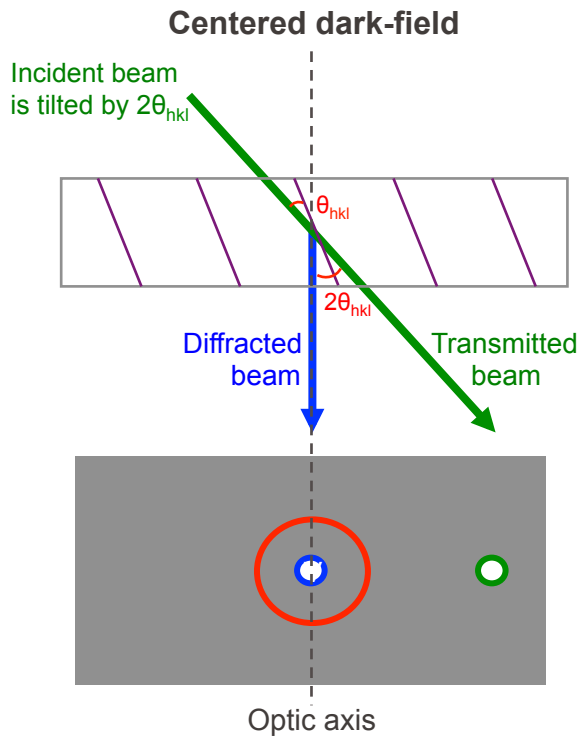
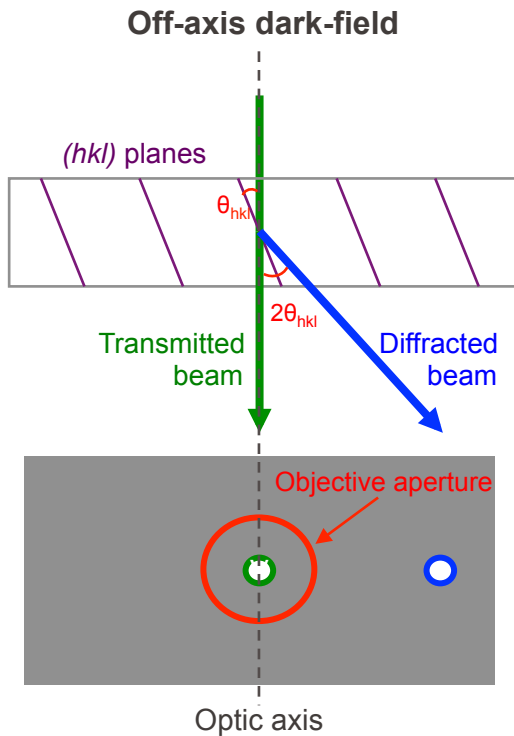
Imaging modes: Dark-field



Dark-field imaging with tilted beam

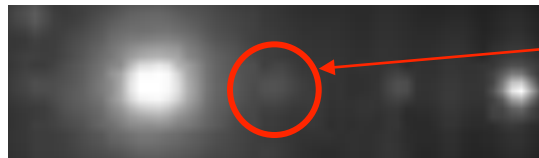
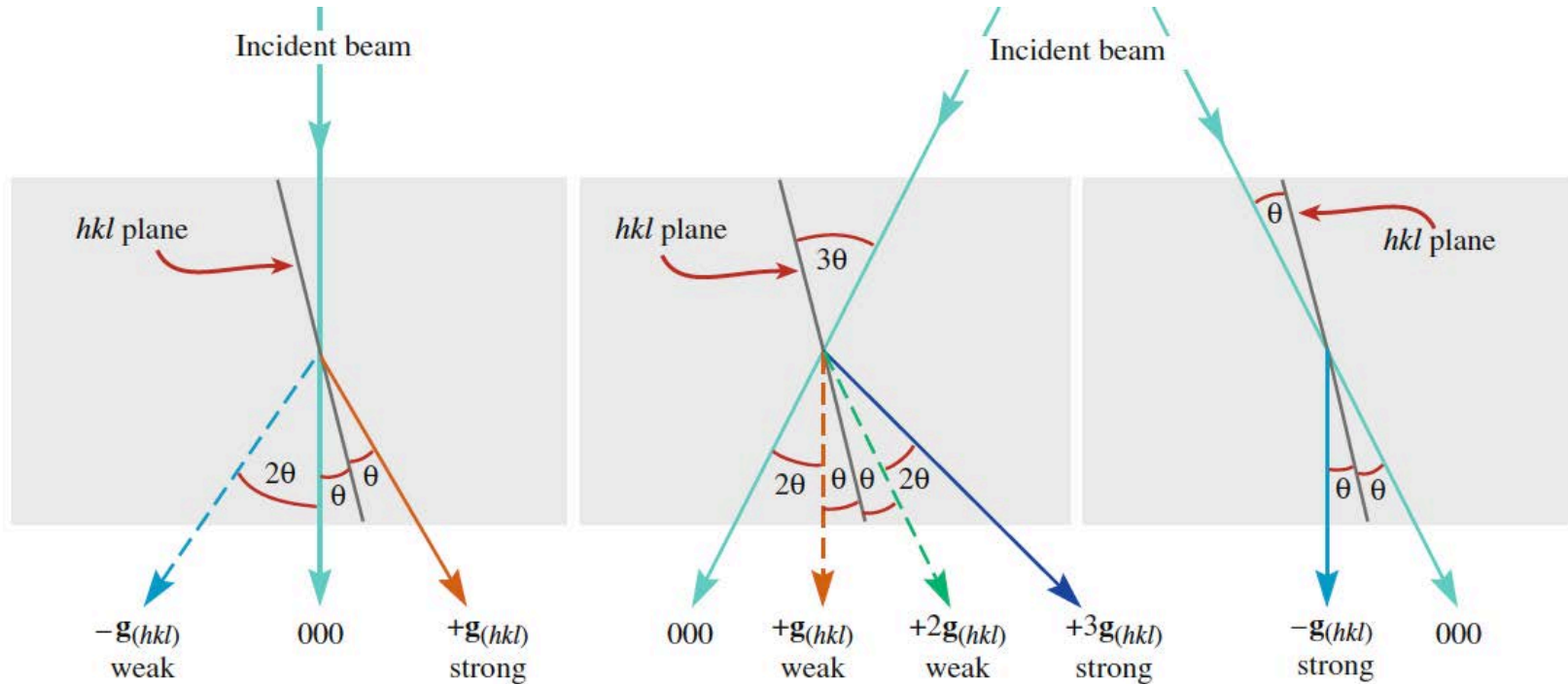
Two ways to setup a dark-field image:

- Off-axis: Shift aperture to diffracted beam:
- Centered dark-field beam tilt: Use electromagnetic deflectors to tilt the incident beam on the sample
→ diffracted beam on the optical axis



Which method produces fewer distortions, i.e. has better spatial resolution?

Imaging modes: Weak-beam dark-field



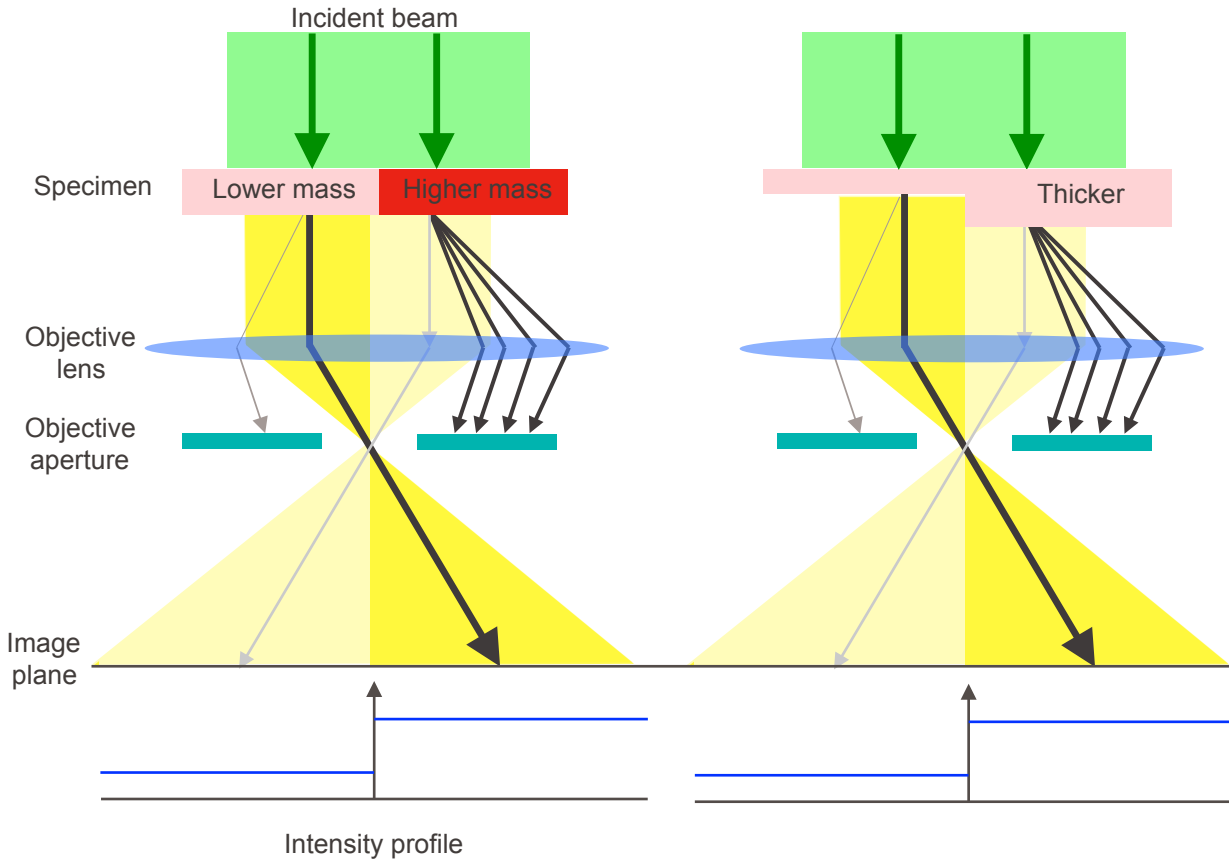
Objective aperture selects the weak reflection that is tilted to the the optic axis

■ Image formation in TEM

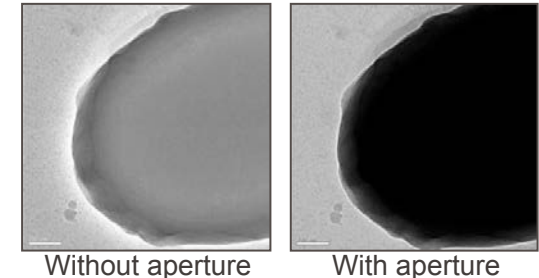
- Image and diffraction modes
- Bright- and dark-field modes
 - Strong- and weak-beam
- High-resolution TEM

■ Image contrast in TEM

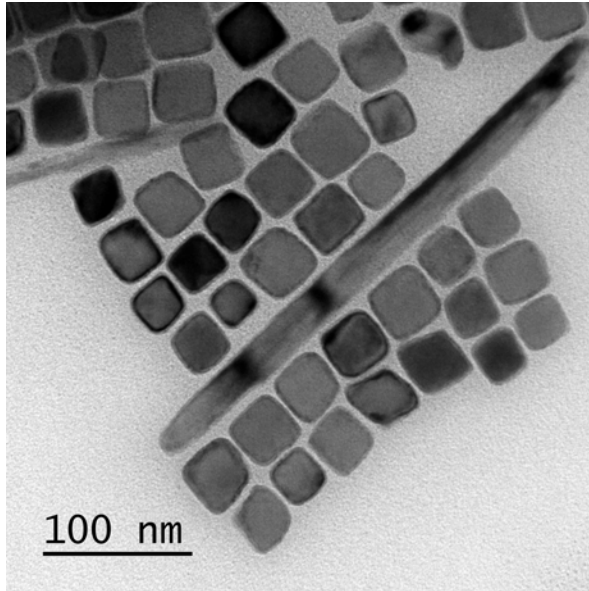
- Mass-thickness contrast
- Diffraction contrast
- Phase contrast



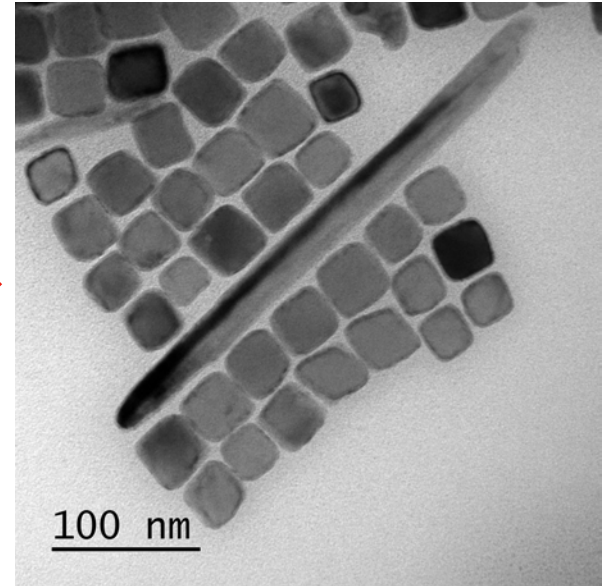
- Areas of higher mass/thickness scatter electrons more than others.
- Electrons are captured by the aperture and lost from the beam path.
- Areas of higher mass thickness will therefore appear dark in the image.
- This is known as:
 - **mass thickness contrast,**
 - **scattering contrast,**
 - **aperture contrast or**
 - **amplitude contrast!**
- Applies to both Crystalline and Amorphous materials.



Example: Copper nano particles



Tilting the sample

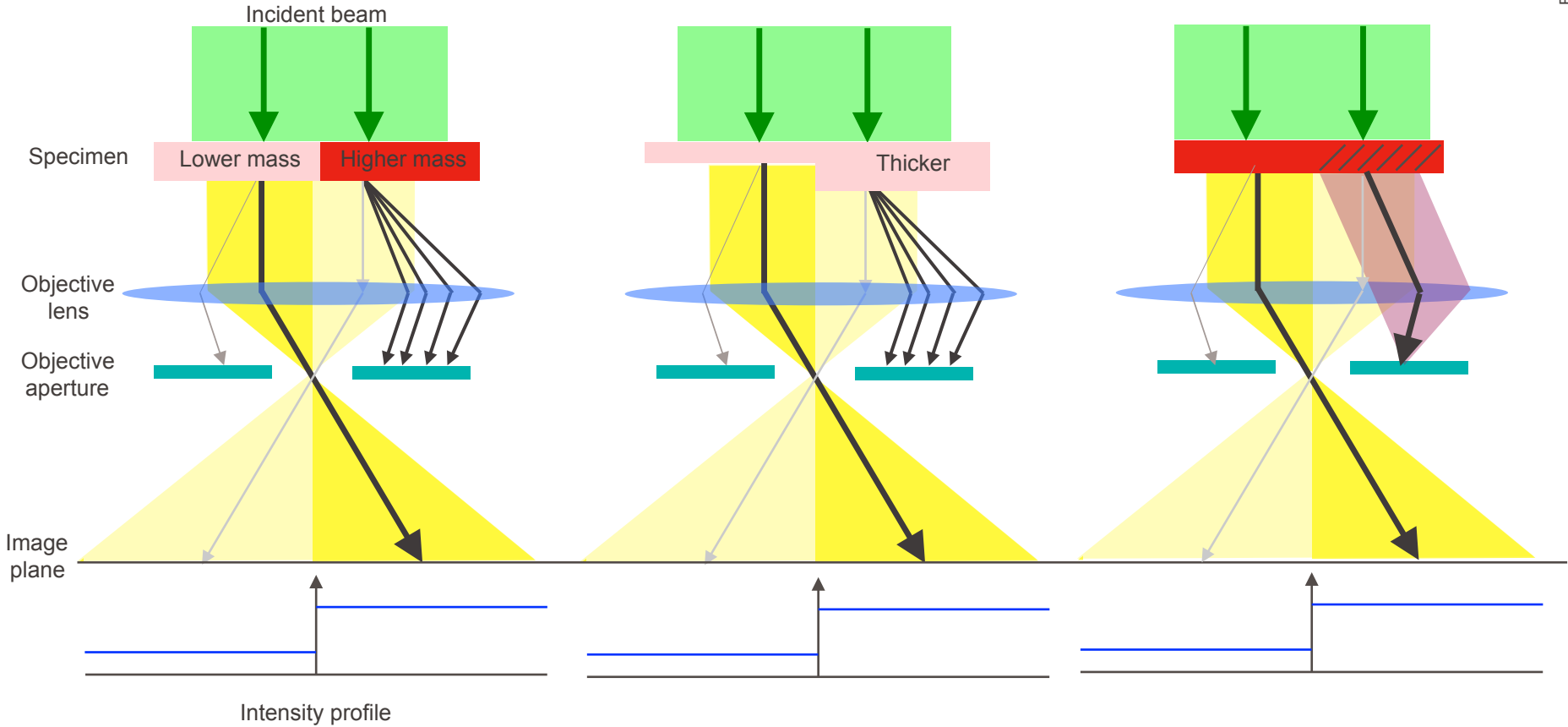


Why some of cubic particles appear darker than others?

Note that contrast changes when tilting the specimen

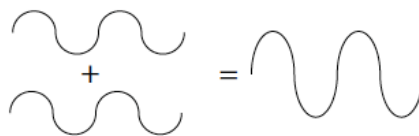
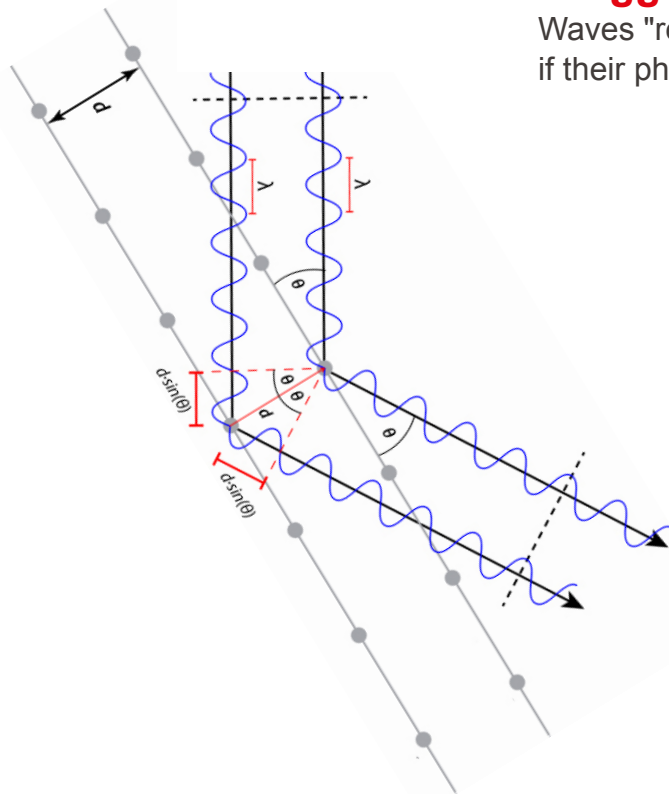
Mass / Thickness contrast

Diffraction contrast



Bragg's law (William Bragg, Nobel Prize Physics, 1915)

Waves "reflected" of lattice planes with a spacing $d_{(hkl)}$ interfere constructively if their phase difference is a multiple of the wavelength λ .



Constructive interference

$$\text{Bragg's law: } n\lambda = 2d_{hkl}\sin\theta$$

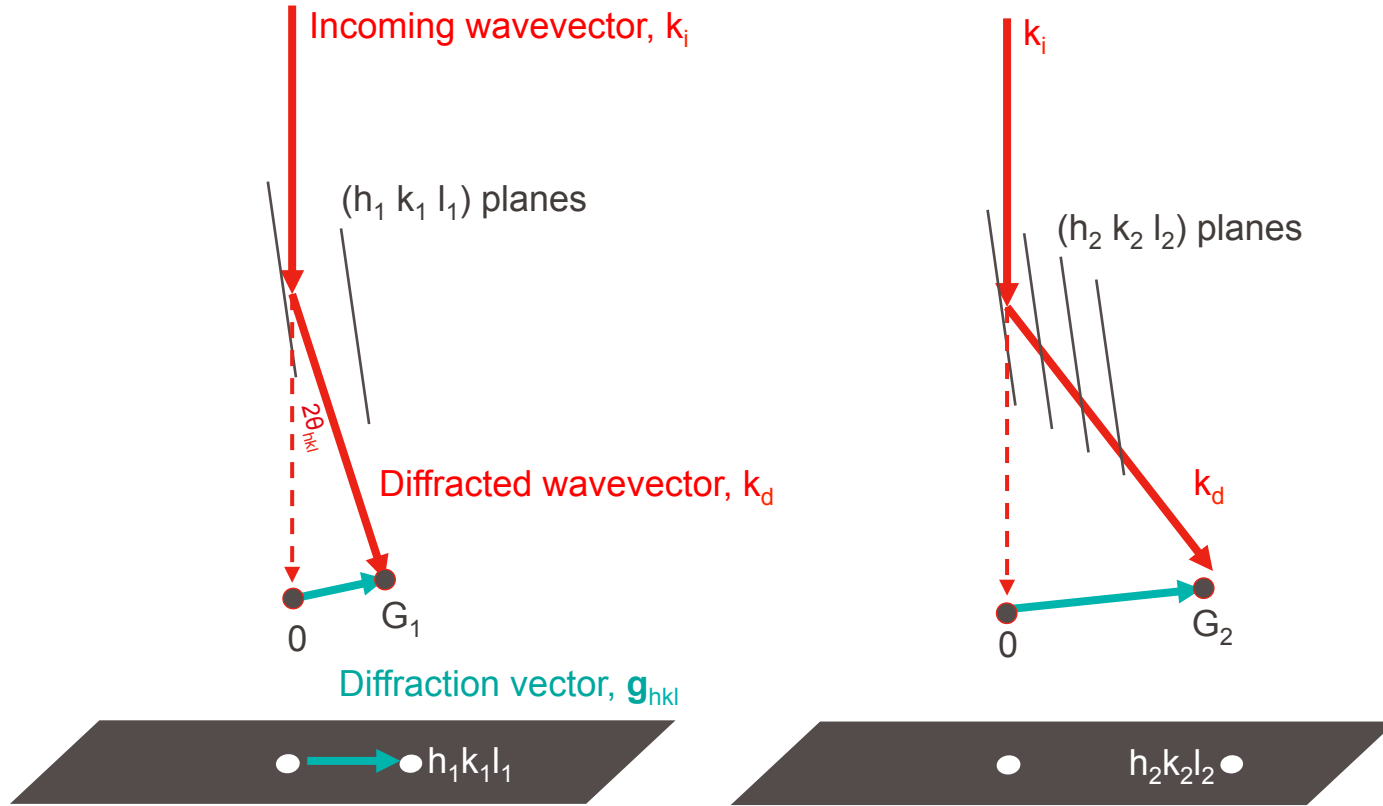
Electron diffraction: $\lambda \sim 2\text{--}3 \text{ pm}$

therefore: $\lambda \ll d_{hkl}$

\Rightarrow small angle approximation: $n\lambda \approx 2d_{hkl}\theta$

Reciprocity: scattering angle $\theta \propto d_{hkl}^{-1}$

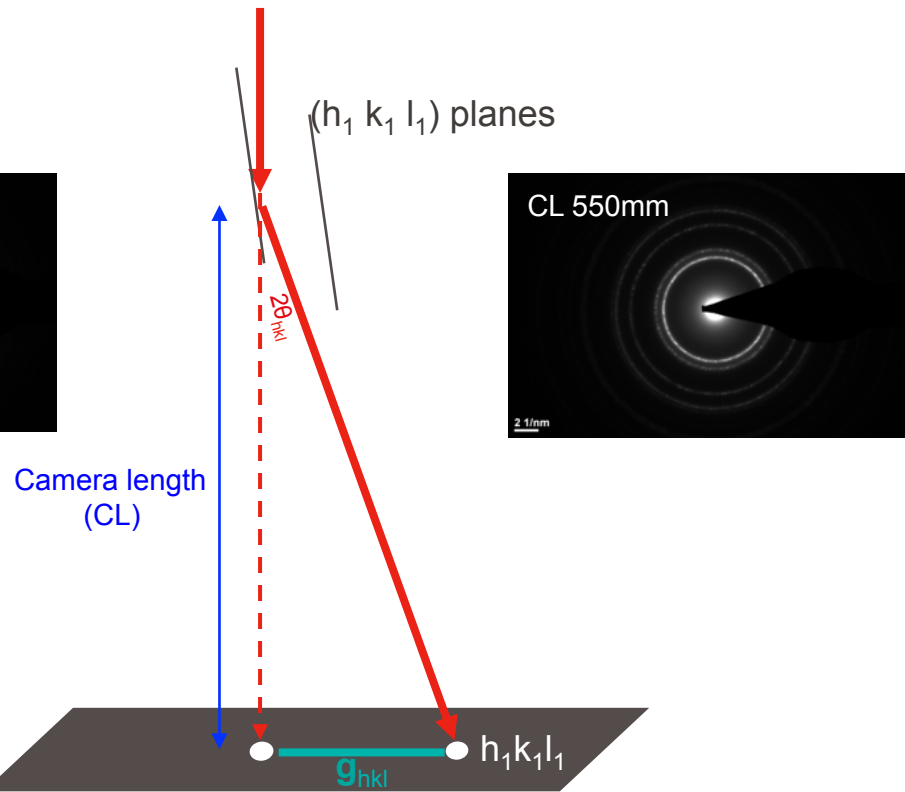
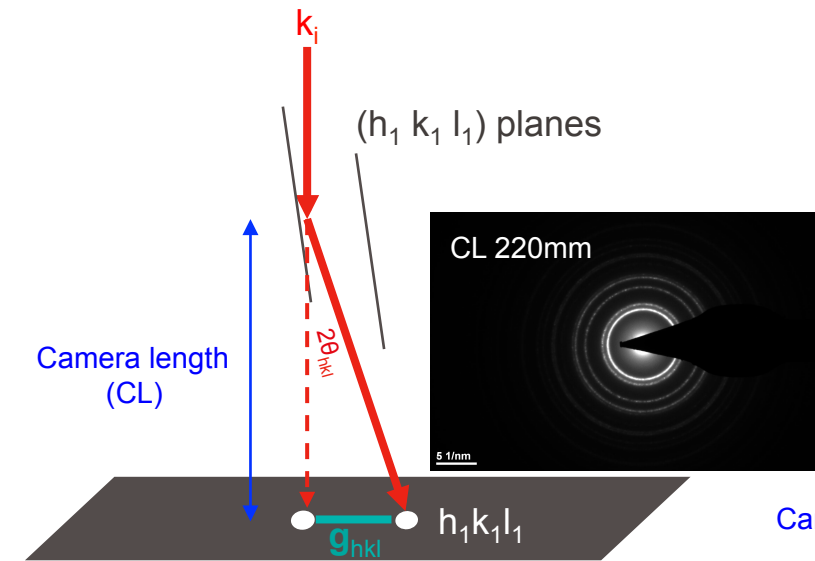
Atomic planes closer together \Rightarrow scattering angles greater



Atomic planes closer together = Greater scattering angle

Reciprocity: scattering angle $\theta_{hkl} \propto d_{hkl}^{-1}$

The magnification of the diffraction pattern (DP) is represented by the camera length CL.
The intermediate and projective lenses allow us to project the DP on the detector and change the CL.



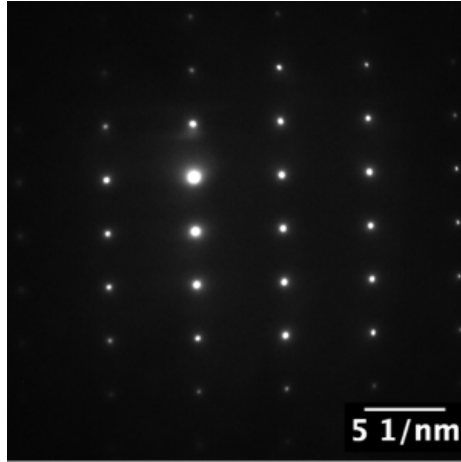
$$\tan(2\theta_{hkl}) = g_{hkl}/CL$$

For small angles, $\theta \approx \sin\theta \approx \tan\theta \approx g/CL$

$$\text{Bragg's law: } 2d_{hkl}\sin\theta_{hkl} = n\lambda$$

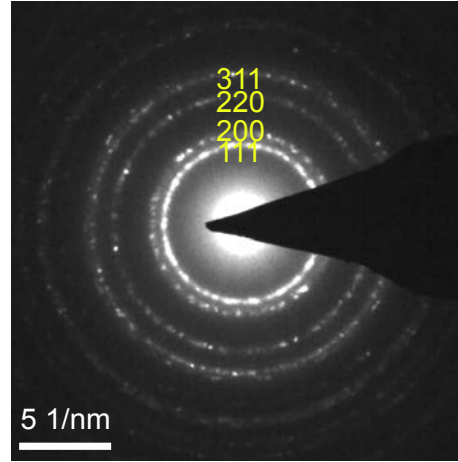
$$d_{hkl} g_{hkl} = \lambda CL$$

Monocrystal



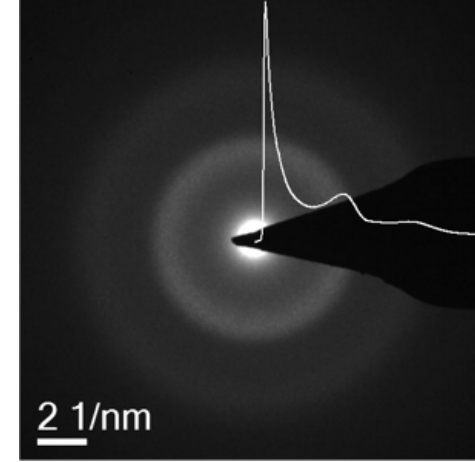
Oriented along a zone axis many (hkl) planes in diffraction conditions. Spot represent different (hkl) planes.

Polycrystalline



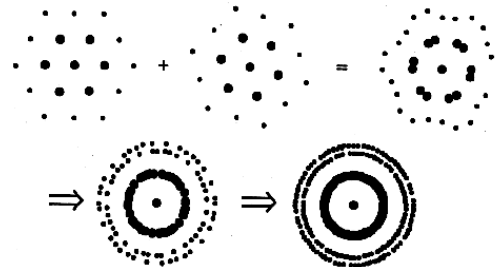
Ring pattern as many crystallites oriented differently in diffraction conditions. Each ring represents one set of (hkl) planes

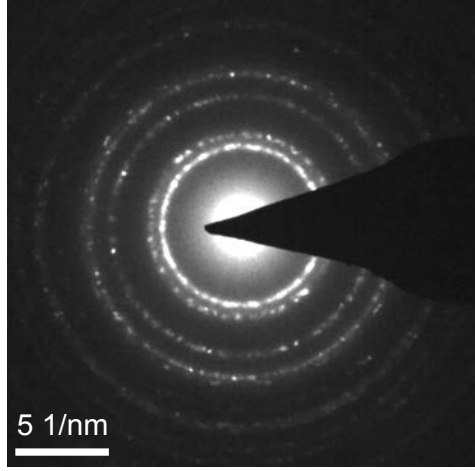
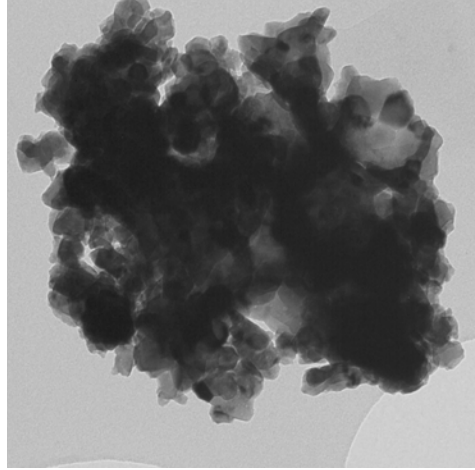
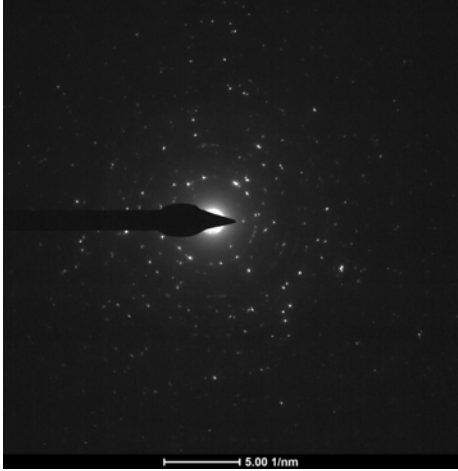
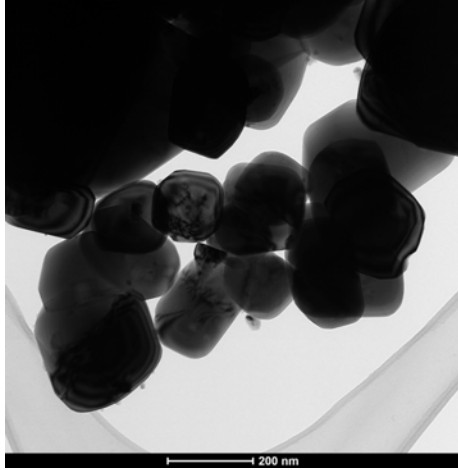
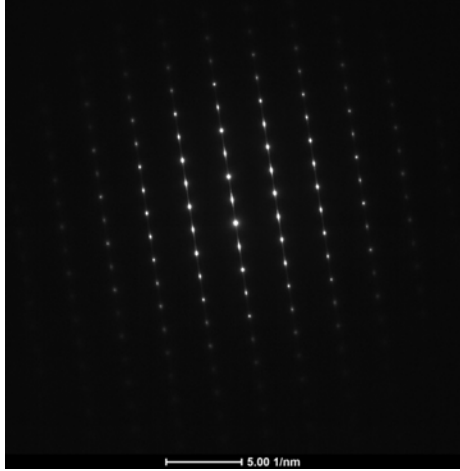
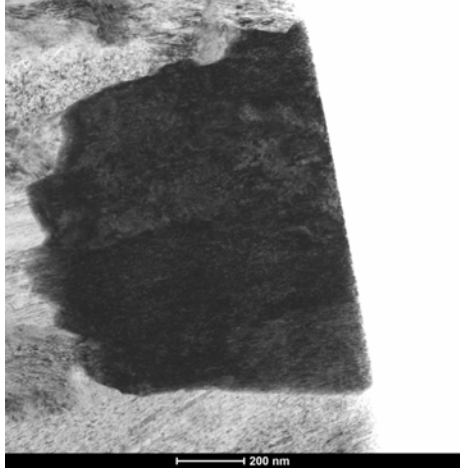
Amorphous



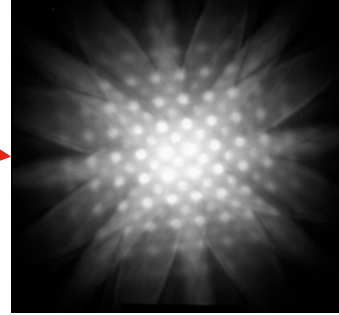
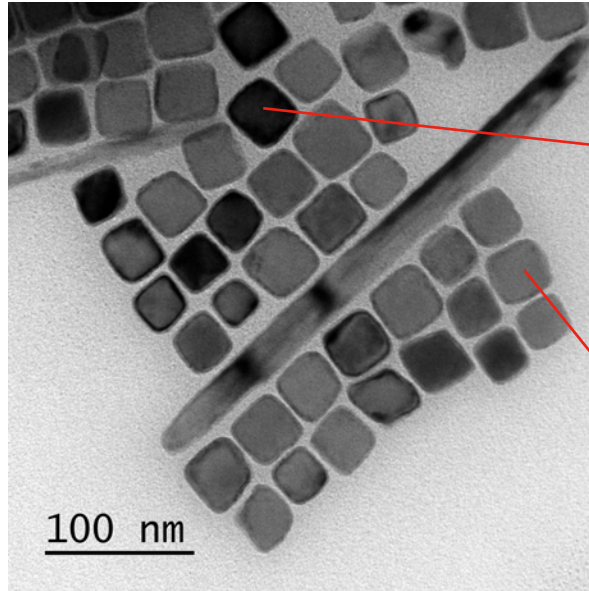
Diffuse ring due to short-range order as interatomic distance \sim constant
Radial distribution function

$$(hkl) \text{ ring's radius} = d_{hkl}^{-1}$$

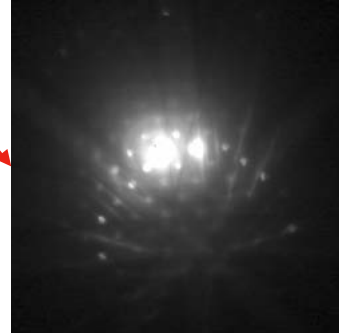




Example: Copper nano particles



Crystal in the strongly diffracting condition:
Low intensity direct beam →
Dark crystal in the bright-field image

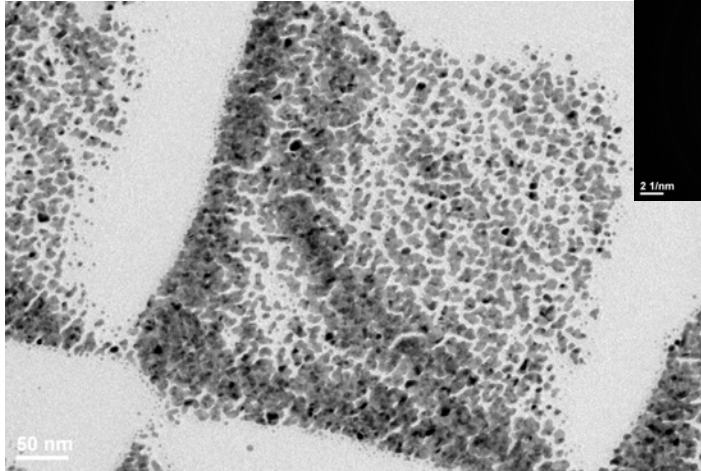


Crystal out of strongly diffracting condition:
Higher intensity direct beam

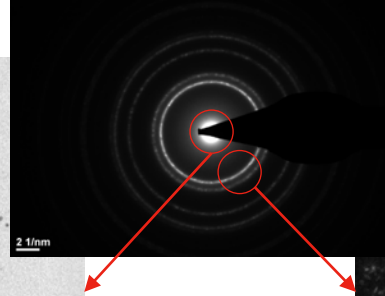
Diffraction condition changes when tilting the specimen

Diffraction contrast: Bright- and dark-field images

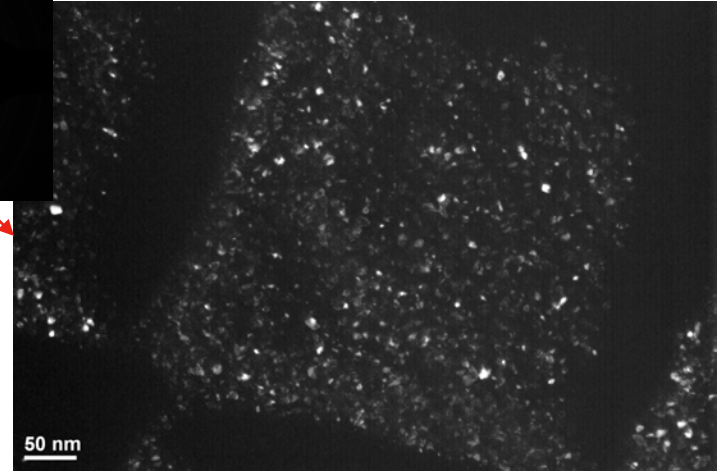
Bright-field image



- Strongly diffracting crystals: dark
- Removes ghost image

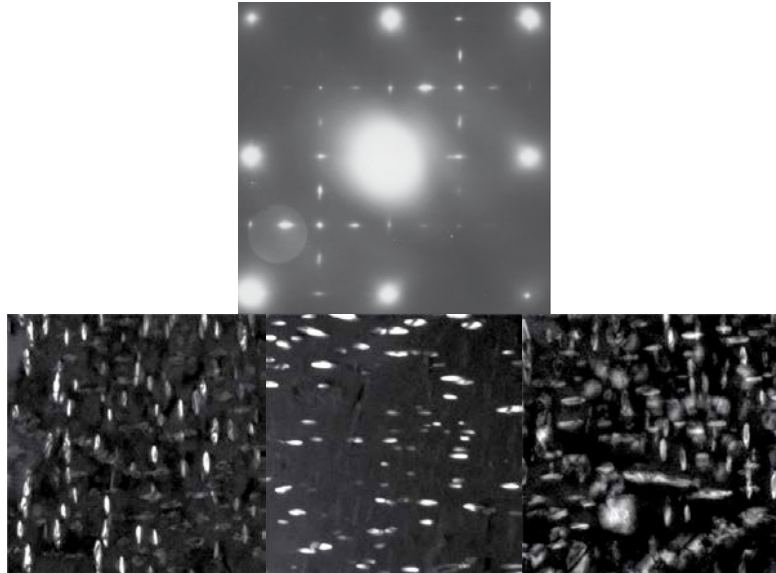


Dark-field image

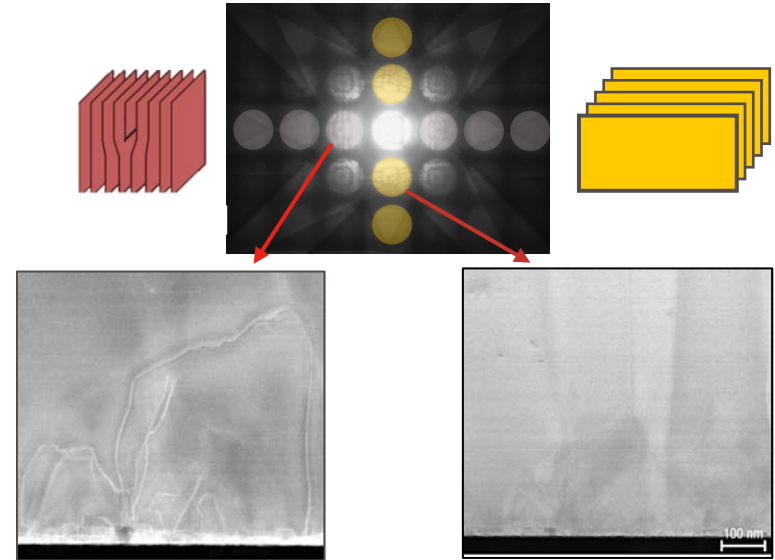


- Only crystals strongly diffracting into objective aperture: bright
- Possibility of crystal phase/orientation discrimination

Map intensity in the diffracted beam



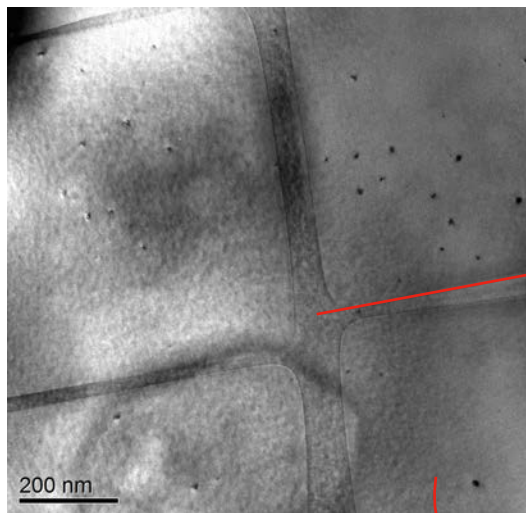
Crystal phase/orientation discrimination



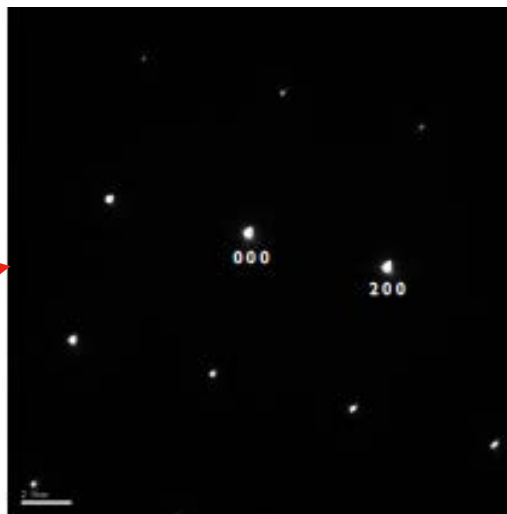
Crystal's defect imaging/analysis

Crystal phase discrimination Example: Ni_3Al -based superalloy

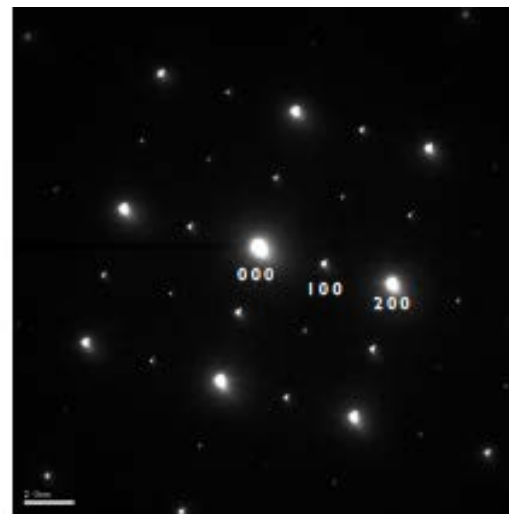
Bright-field



γ -phase matrix: FCC
(Ni, Al disordered on sites)

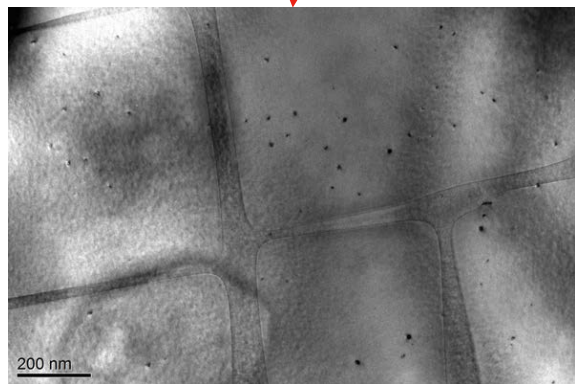
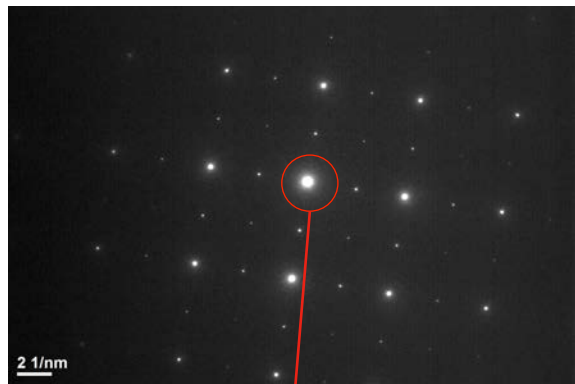


γ' -phase precipitate: primitive cubic
(Ni on face centres, Al on corners)

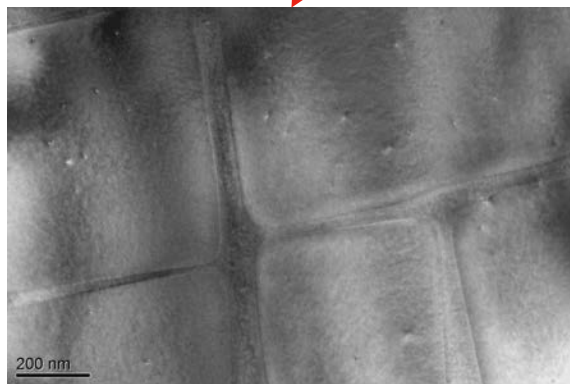
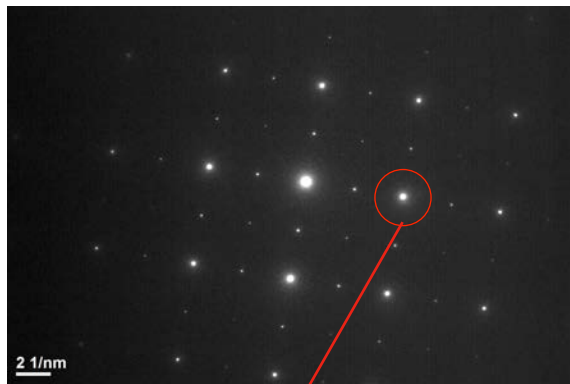


Note: EDX can't discriminate these two crystal phases!

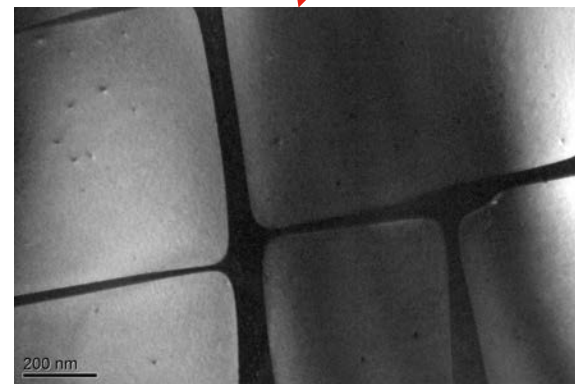
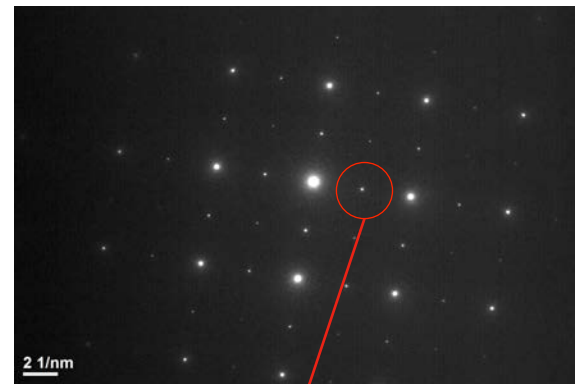
Crystal phase discrimination Example: Ni_3Al -based superalloy



Bright-field image



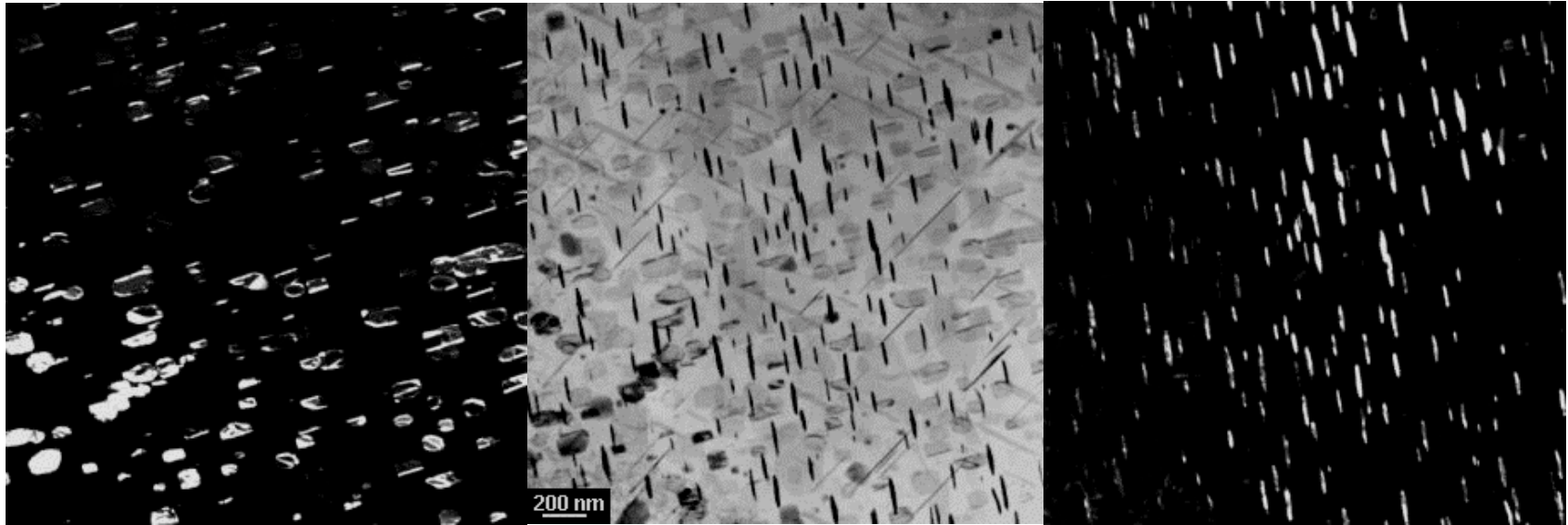
Dark-field image $\mathbf{g} = (2\ 0\ 0)$



Dark-field image $\mathbf{g} = (1\ 0\ 0)$

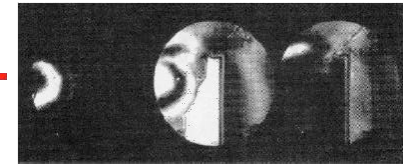
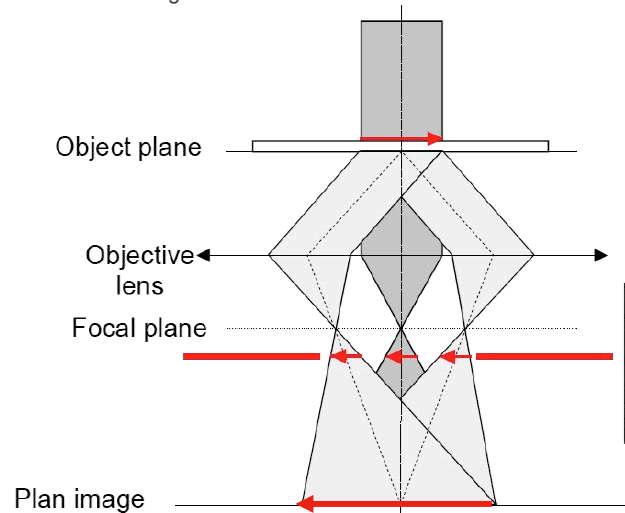
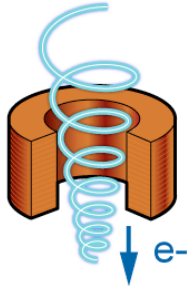
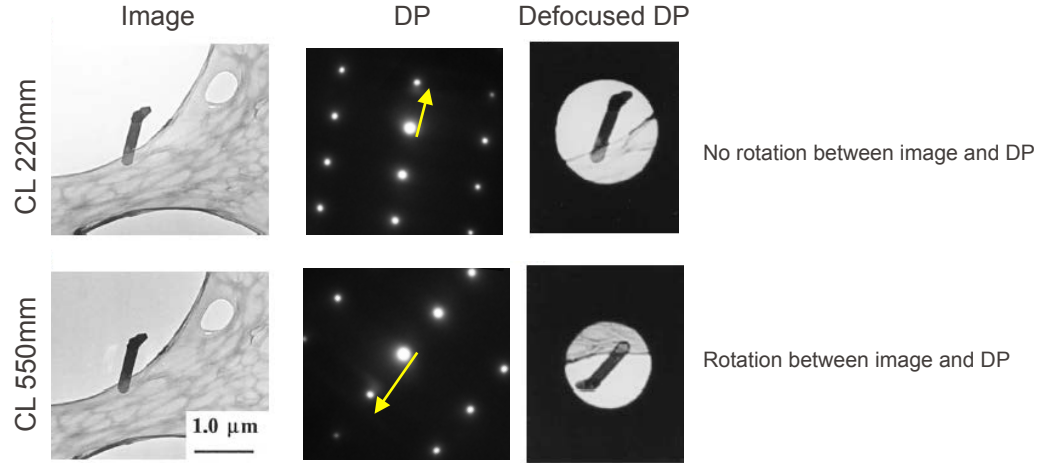
Crystal phase and orientation discrimination

Example of aluminum alloy containing precipitates with preferential growth direction



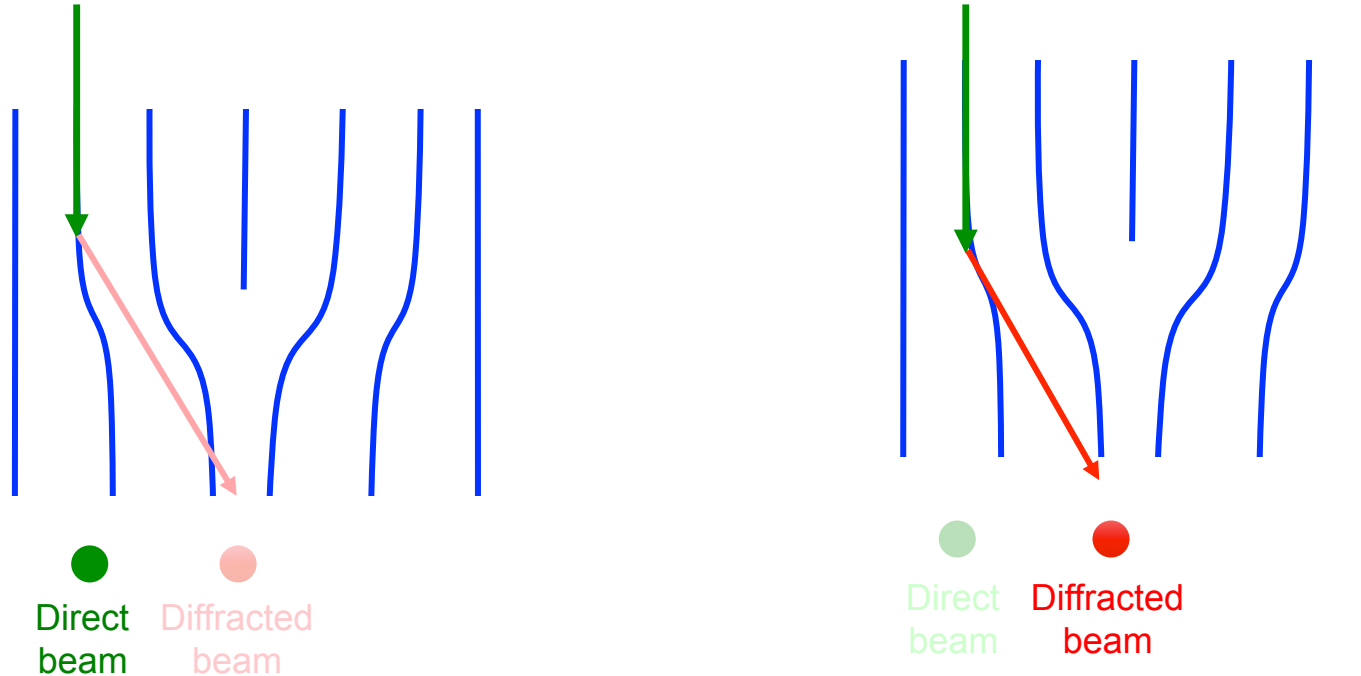
Orientation relationship between the matrix and precipitates can be determined

Calibration of rotation between the image and diffraction is necessary.



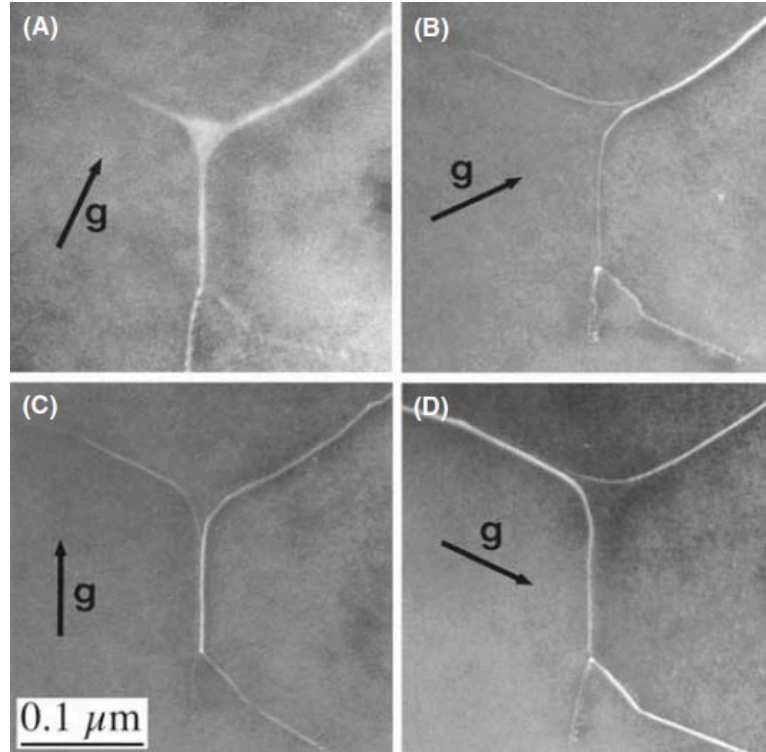
Defocused diffraction pattern

Crystal's defect imaging/analysis
Specimen is at near-Bragg condition

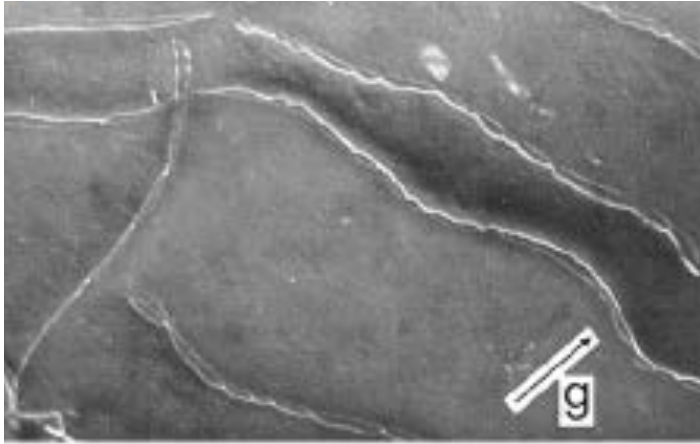


Near dislocation core, crystal is distorted and is at the exact Bragg condition:
intensity in diffracted beam and hence image increases

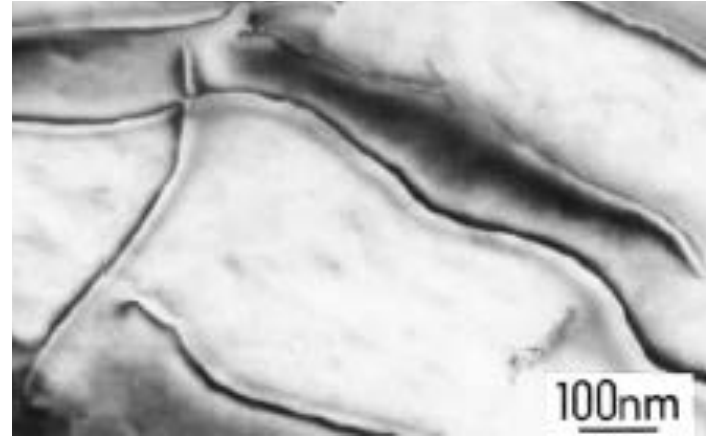
Crystal's defect imaging/analysis
Example: Pairs of dislocation nodes in a Cu alloy



Comparison of dislocation images in Cu alloy



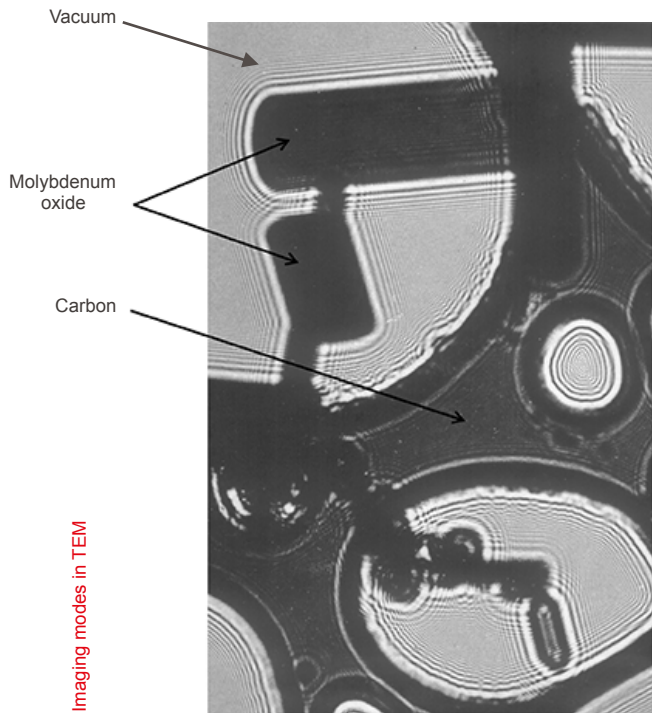
Weak-beam dark-field



Strong-beam dark-field

Will be discussed on Wednesday by Dr. Duncan Alexander

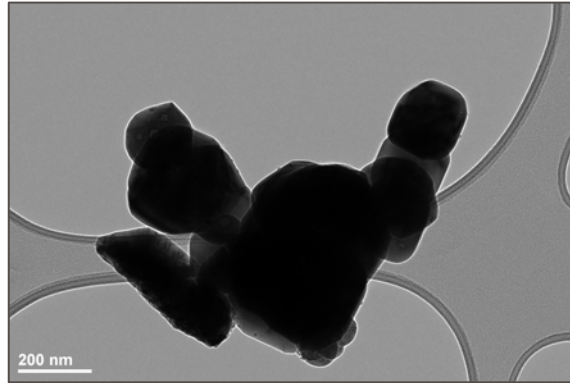
What happens when an electron wave passes through the sample?



Molybdenum oxide particles on a holey carbon grid at 80kV

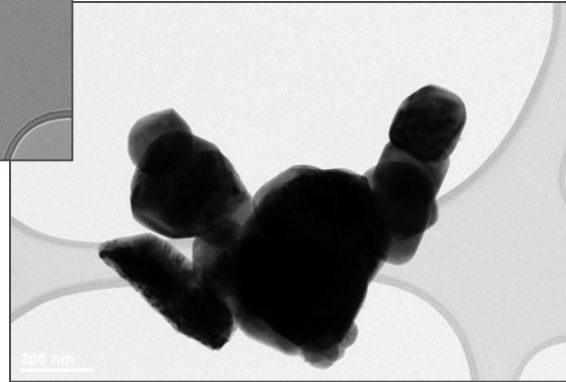
A spherical wave scattered from the edge of a specimen interferes with the incident wave. Then, interference fringes are produced whose period becomes narrow with the distance from the edge of the specimen.

Fringes arise due to the high coherence of the electron beam and interface of two electron waves that are scattered differently, e.g. one which is not scattered (vacuum) and one that scatters off the edges of sample features (the hole in this example), resulting in a path length difference.

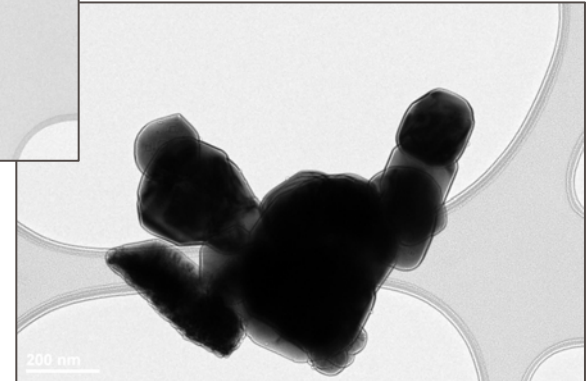


Under-focused
Uniform white fringes

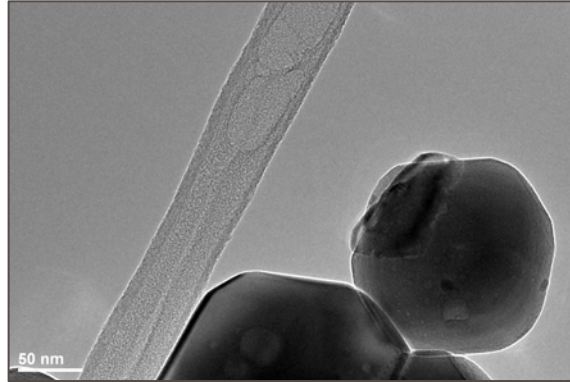
Bright or dark fringe thickness depends on focus!



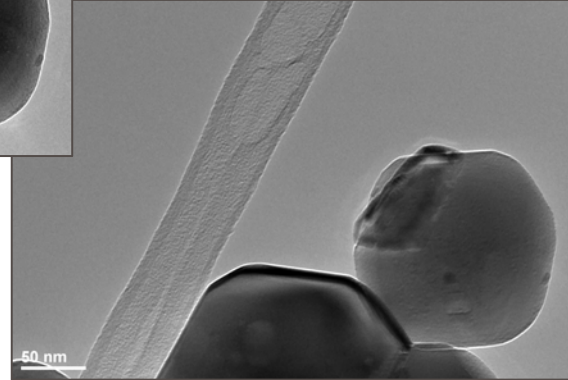
In focus
Min of contrast, no fringes



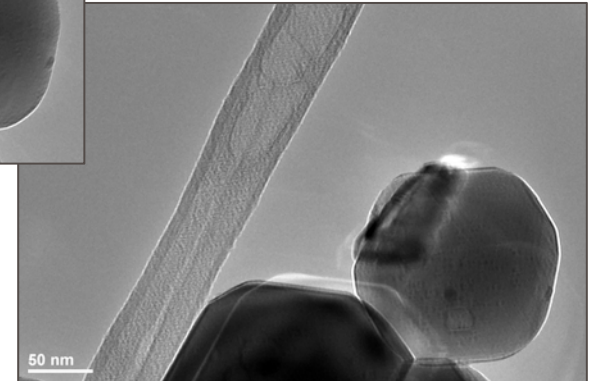
Over-focused
Uniform dark fringes



Without objective astigmatism
Uniform fringes



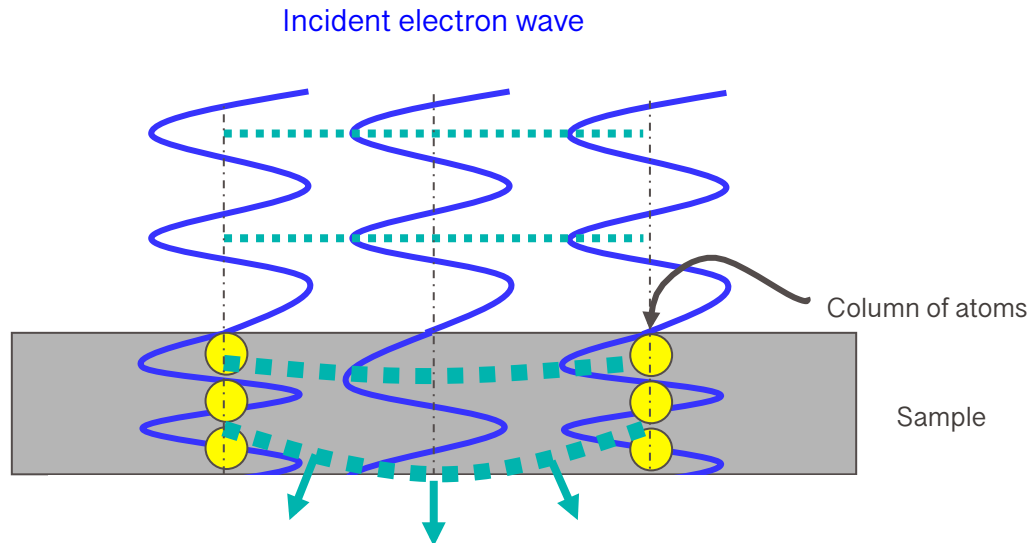
With objective astigmatism
Fringes varying thickness



With large objective astigmatism
Fringes varying

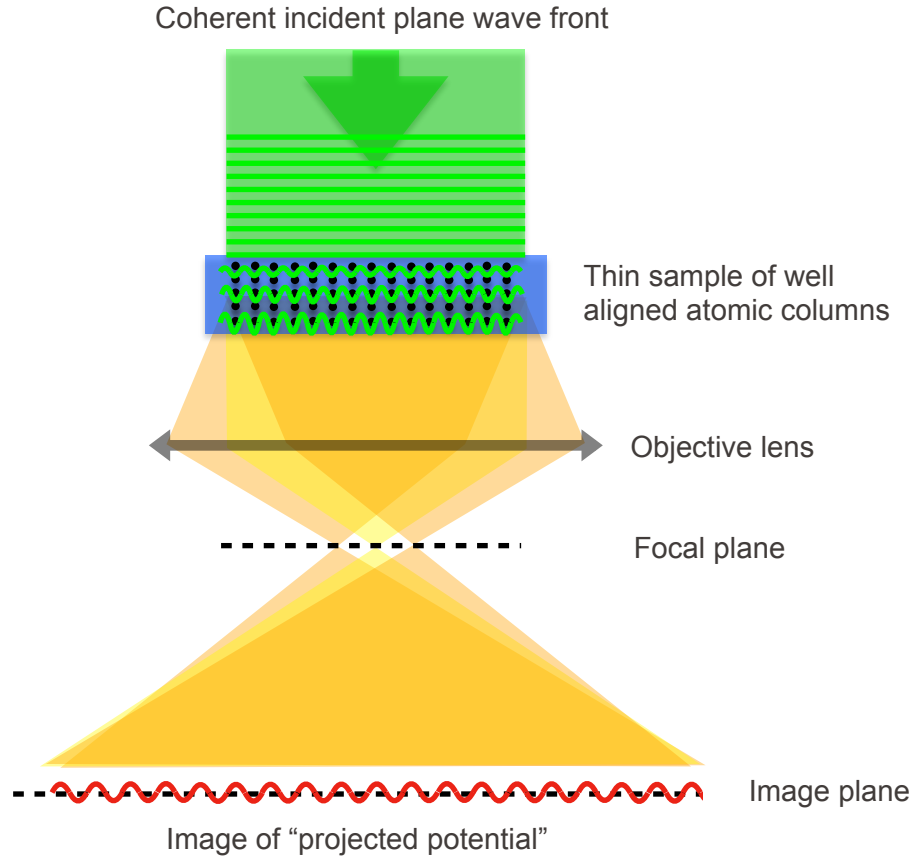
Fringes can also be used to observe and correct the astigmatism of the objective lens.

What happens when an electron wave passes through the sample?

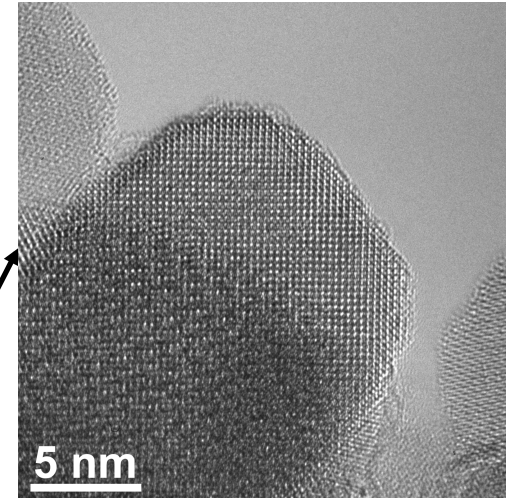


Variations in the projected potential produce local relative phase shifts of the electron wave. The wave front therefore bends as wave travels through medium.

The direction of propagation of the electron may change! \Rightarrow Diffraction!



Due to changes in sample thickness and orientation, as well as lens imperfections, image interpretation is complex.



Lattice fringes in iron oxide nanoparticles

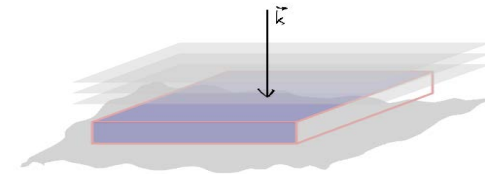
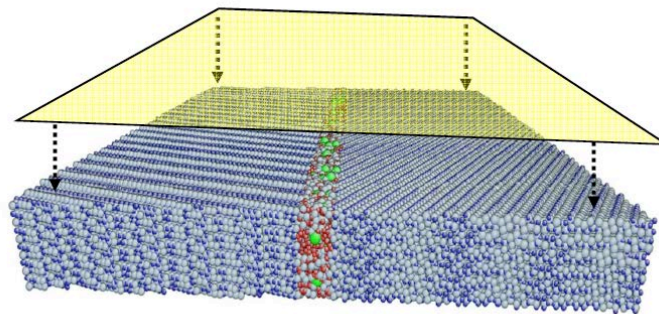
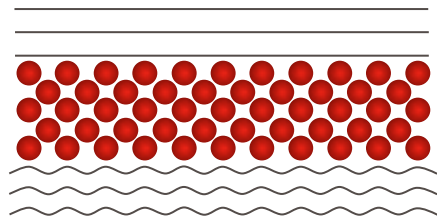
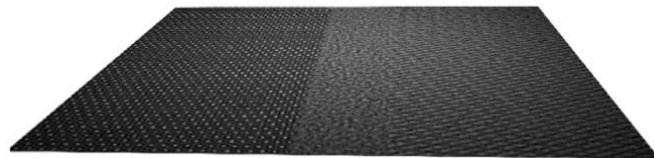


Image forming lens

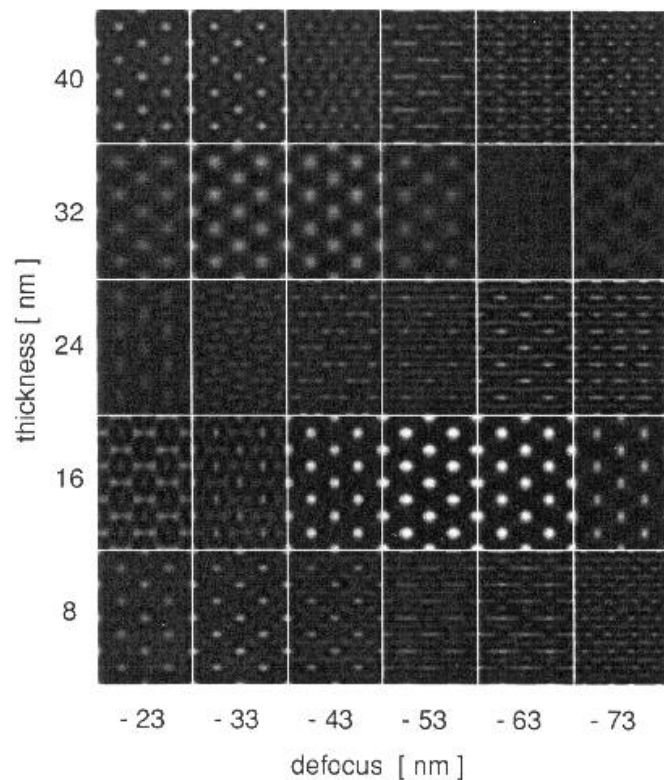
But ...
not a perfect lens!



HRTEM can give you local structural information of your specimen.

However, do not expect straightforward interpretation (dots do not always correspond to atoms).

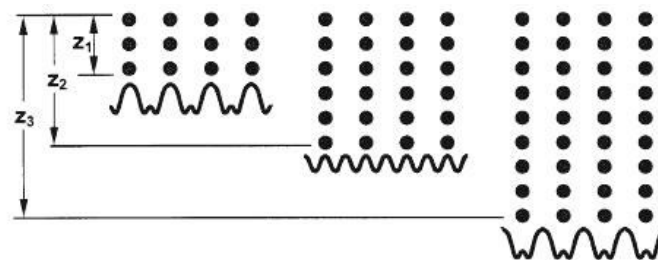
Phase contrast images can be difficult to interpret, because many factors contribute to phase shift:
Thickness, orientation, scattering factor, focus, spherical aberration



Resist the temptation of interpreting the spots as atoms!

The crystal potential serves to phase shift the electron wave locally; and crystal thickness affects phase shifts.

Thus at the crystal exit surface, the electron wave carries information about the crystal potential, projected in the direction of the incident beam.



The objective lens (CTF) determines how much phase signal gets transmitted to the real space wave-function in the image plane.

Mass-Thickness contrast

- Applies for both crystalline and amorphous phase and scales with Z^2t

Diffraction contrast

- Bright-field: objective aperture centered on “unscattered” beam
- Dark-field: objective aperture centered on “diffracted beams”
- Weak Beam Dark-field: sample tilted to excited higher order “3g” reflections to higher intensity and objective aperture centered on low intensity “1g” spot

Fresnel contrast

- Developed by the interference of two waves, reference vacuum wave and one which scatters off the edges in the sample causing a path length difference and phase shift, resulting in fringe patterns that depend on the focus setting of the microscope
- Can be used to correct objective astigmatism

HR-TEM or Phase contrast

- Developed by the interference of two waves, one which undergoes a phase shift due to the interactions with the sample crystal structure of a given thickness and is altered by the microscope aberrations
- Simulations are needed to interpret phase contrast images properly